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(54) **LED CHIP AND MANUFACTURING  
METHOD OF THE SAME**

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(52) **U.S. Cl.**

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(57)

**ABSTRACT**

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(63) Continuation of application No. 18/111,861, filed on Feb. 20, 2023, now Pat. No. 12,288,775, which is a continuation of application No. 16/852,522, filed on Apr. 19, 2020, now Pat. No. 11,587,914.

(60) Provisional application No. 62/847,852, filed on May 14, 2019, provisional application No. 62/869,972, filed on Jul. 2, 2019.

**Publication Classification**

(51) **Int. Cl.**

*H01L 25/075* (2006.01)

*H01L 23/31* (2006.01)

A light emitting device including a board, a first stacked structure configured to emit light having a first wavelength, a second stacked structure configured to emit light having a second wavelength, a third stacked structure configured to emit light having a third wavelength, a first connection electrode electrically connected to the first stacked structure, the second stacked structure, and the third stacked structure, and a protection material covering at least a portion of the first connection electrode, in which each of the first, second, and third stacked structures is configured to selectively emit light while being connected to the first connection electrode, and the protection material is configured to transmit at least 50% of light having the first wavelength, light having the second wavelength, and light having the third wavelength upon operation of each of the first, second, and third stacked structures.

100

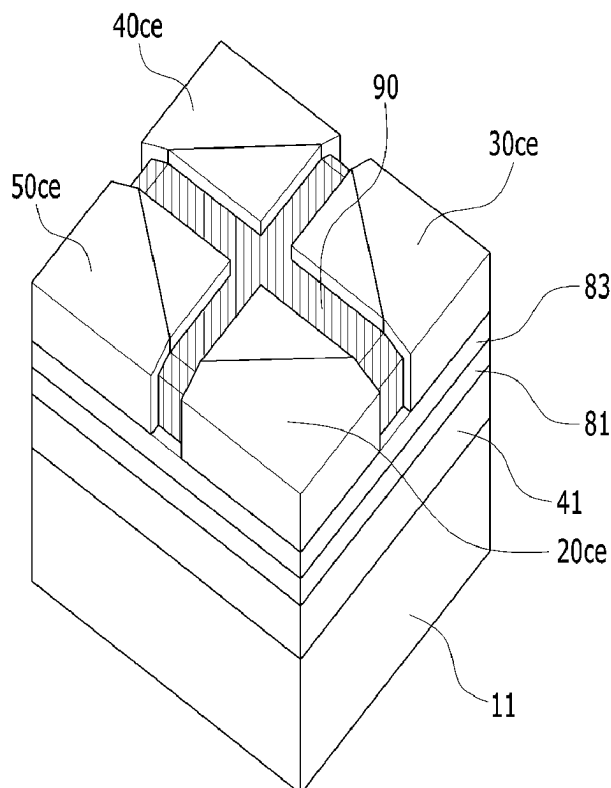


FIG. 1A

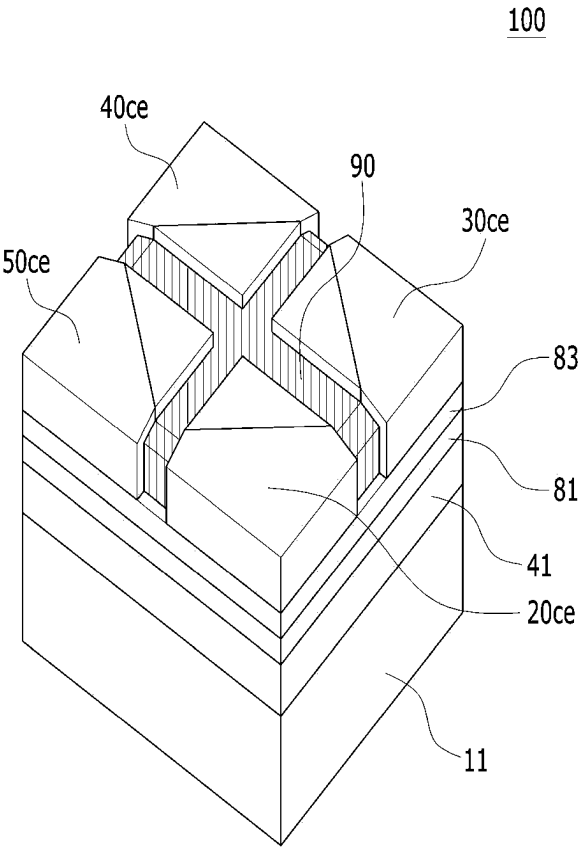
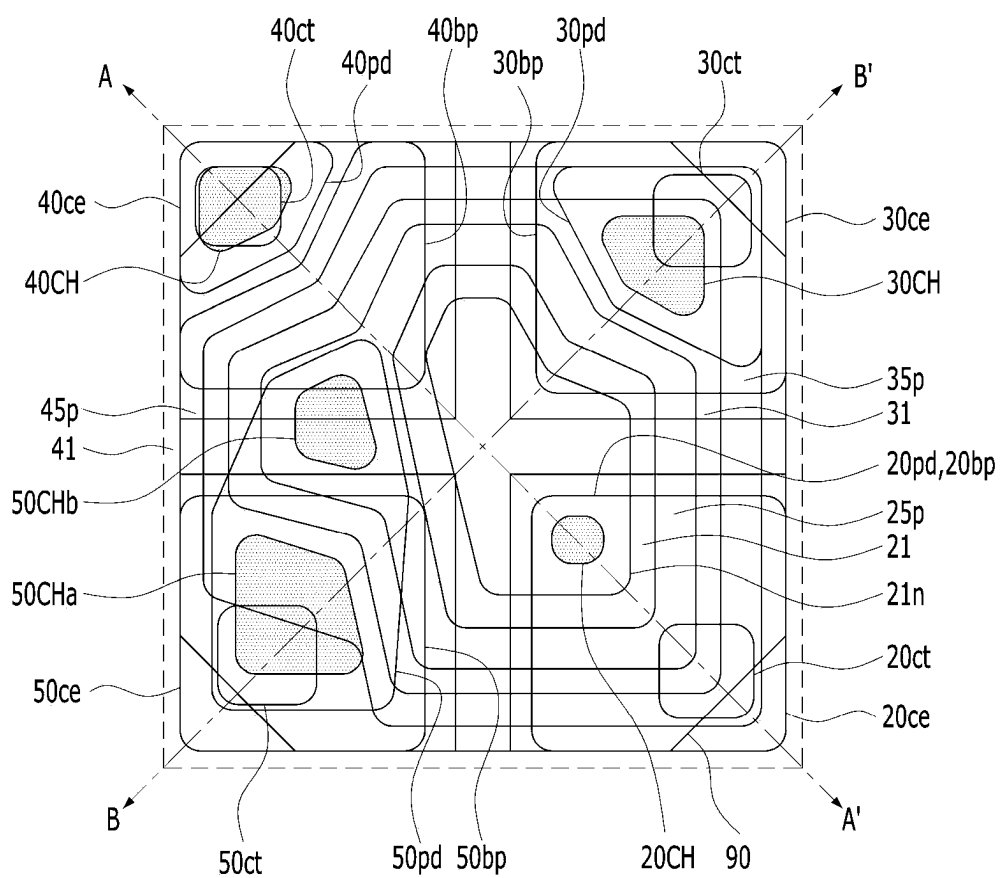
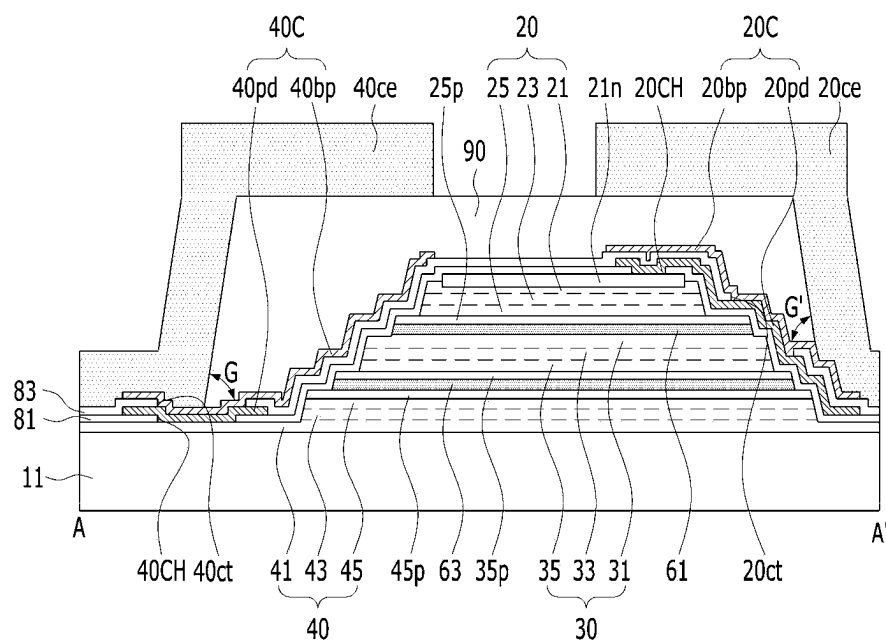


FIG. 1B



**FIG. 1C**



**FIG. 1D**

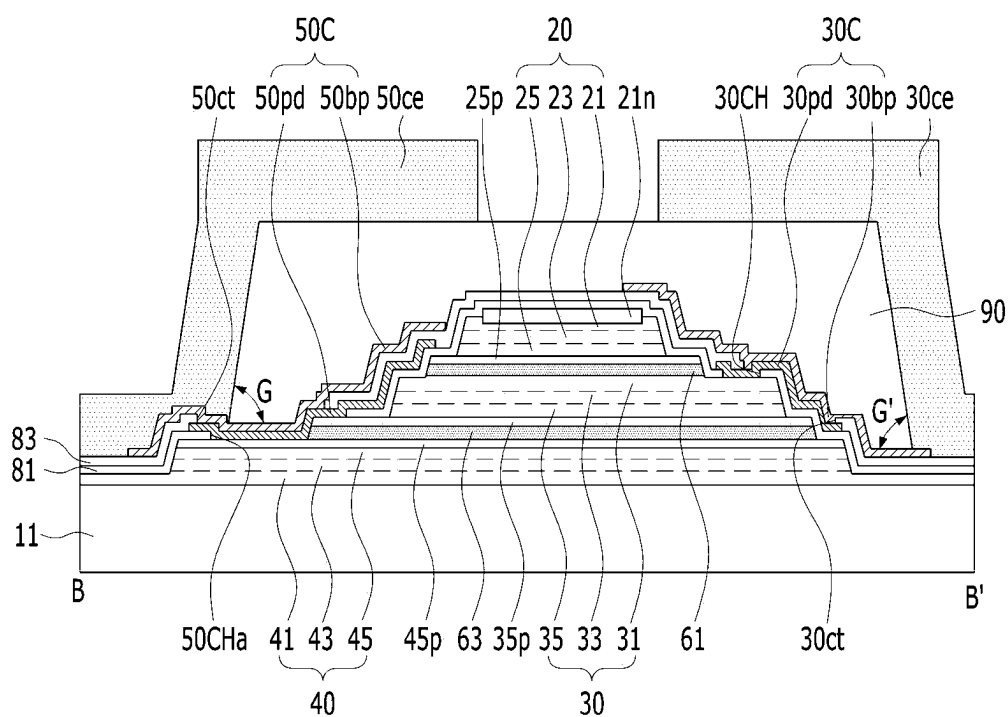


FIG. 1E

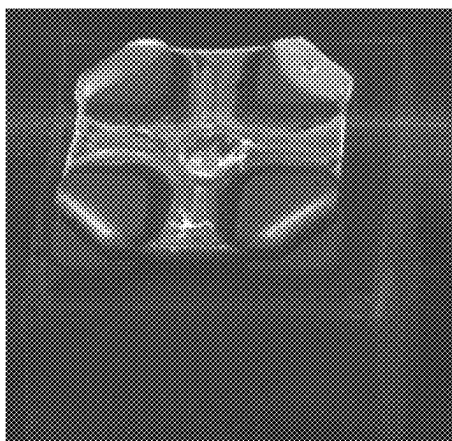
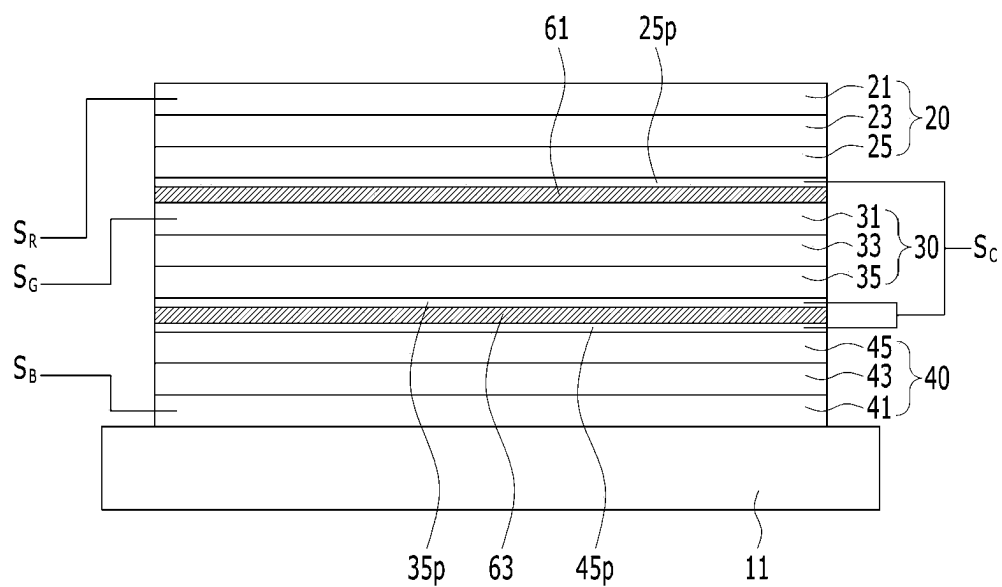
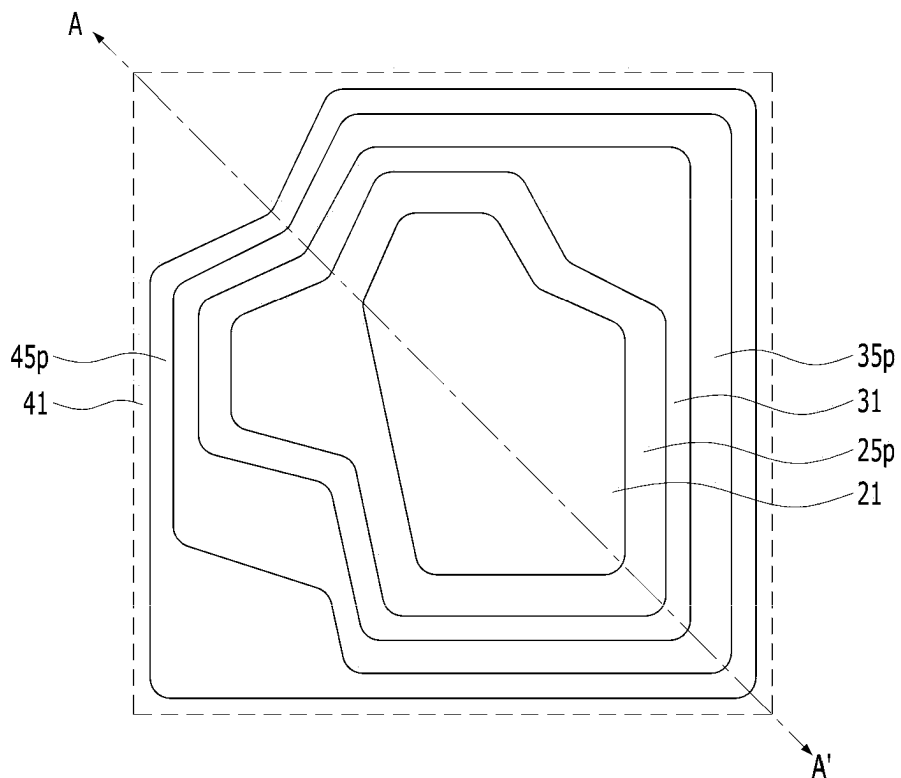


FIG. 2



**FIG. 3A**



**FIG. 3B**

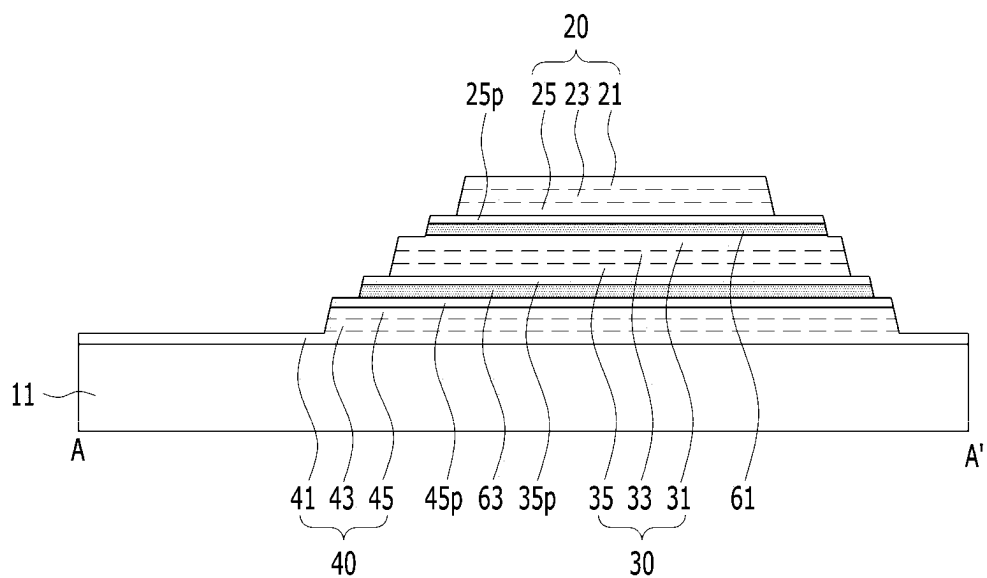


FIG. 4A

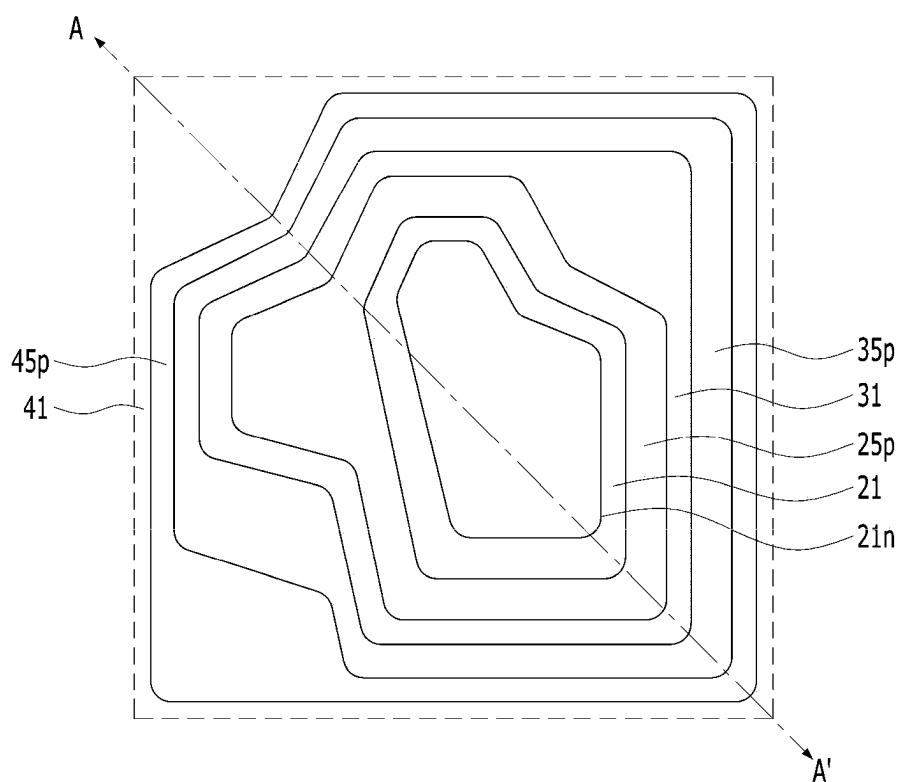


FIG. 4B

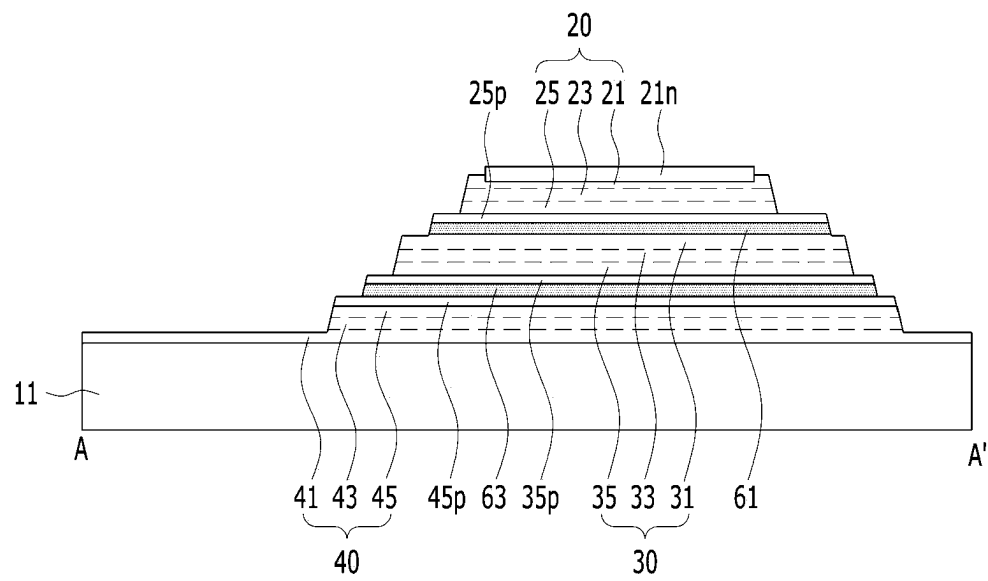


FIG. 5A

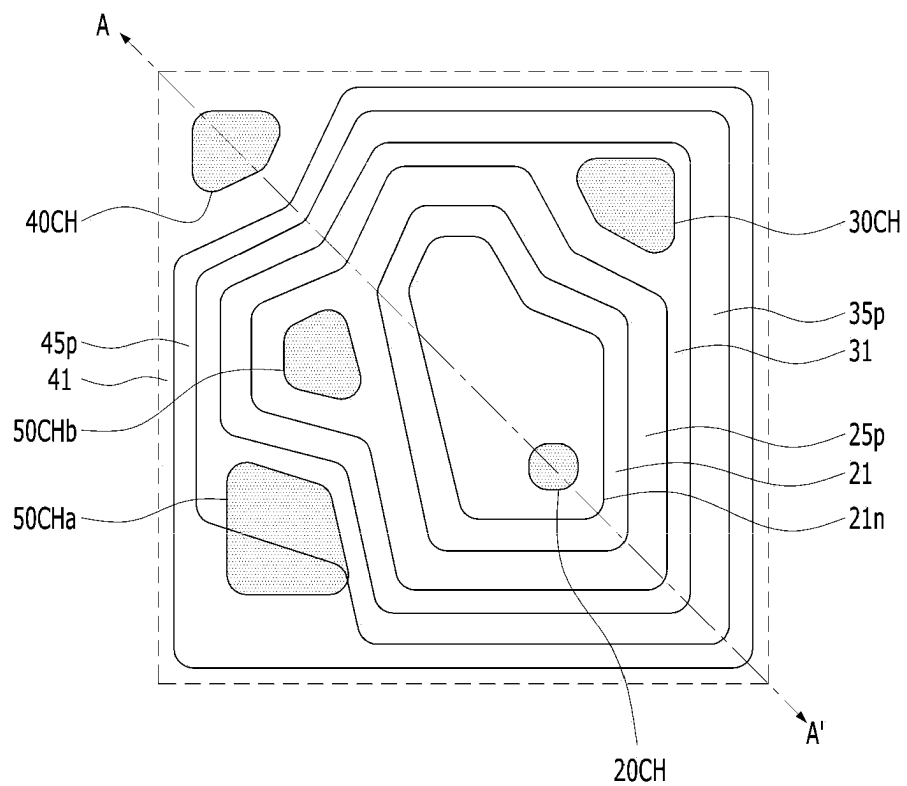
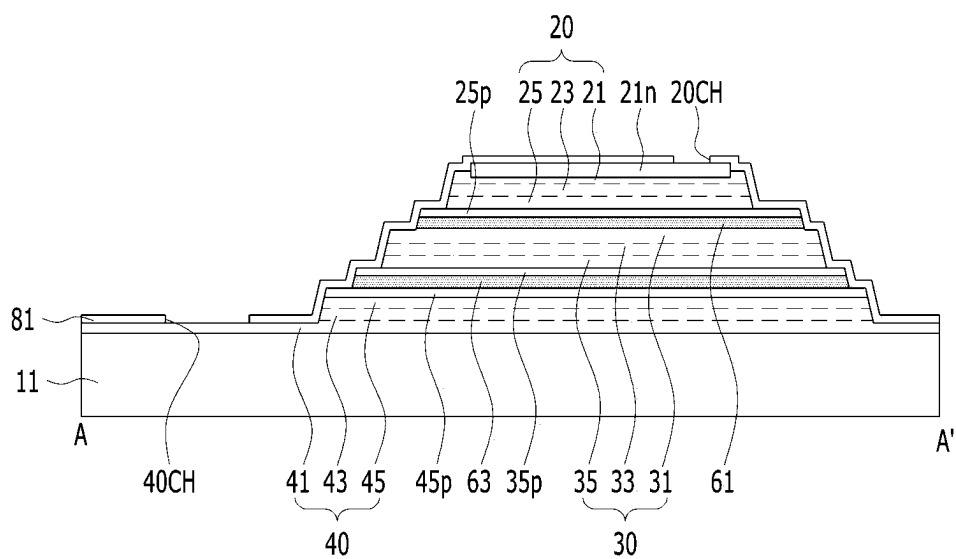
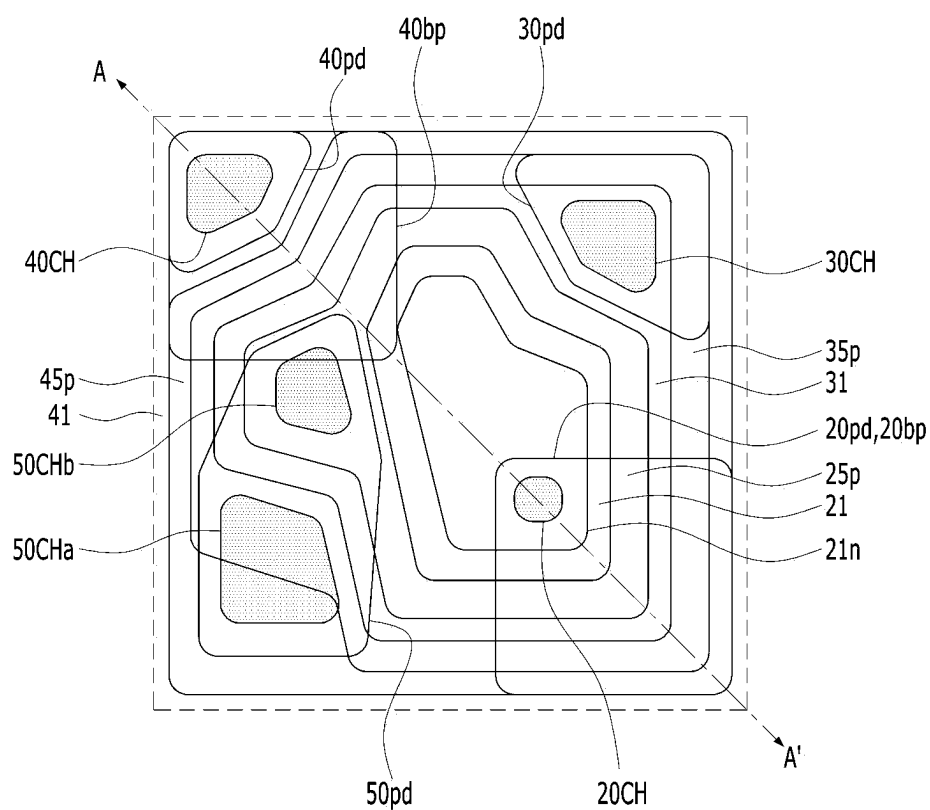


FIG. 5B





**FIG. 6A**



**FIG. 6B**

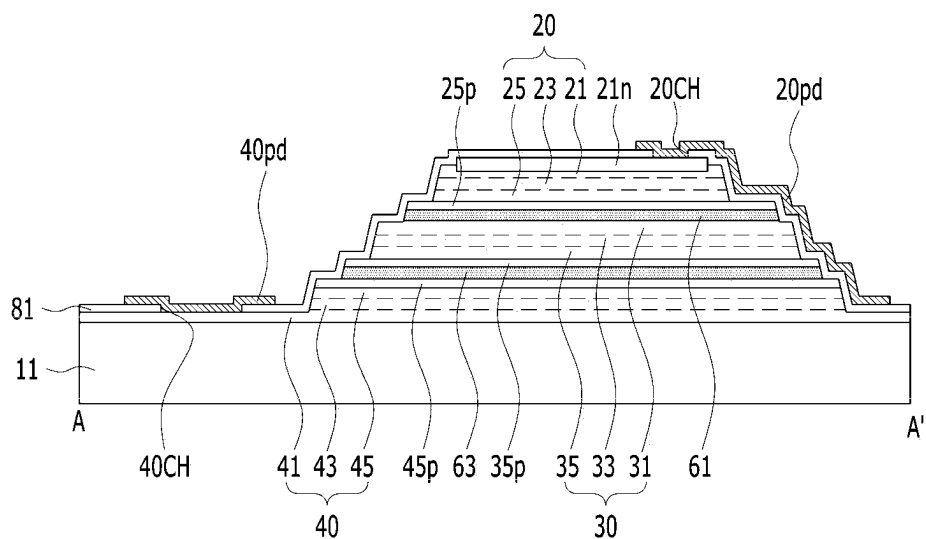


FIG. 7A

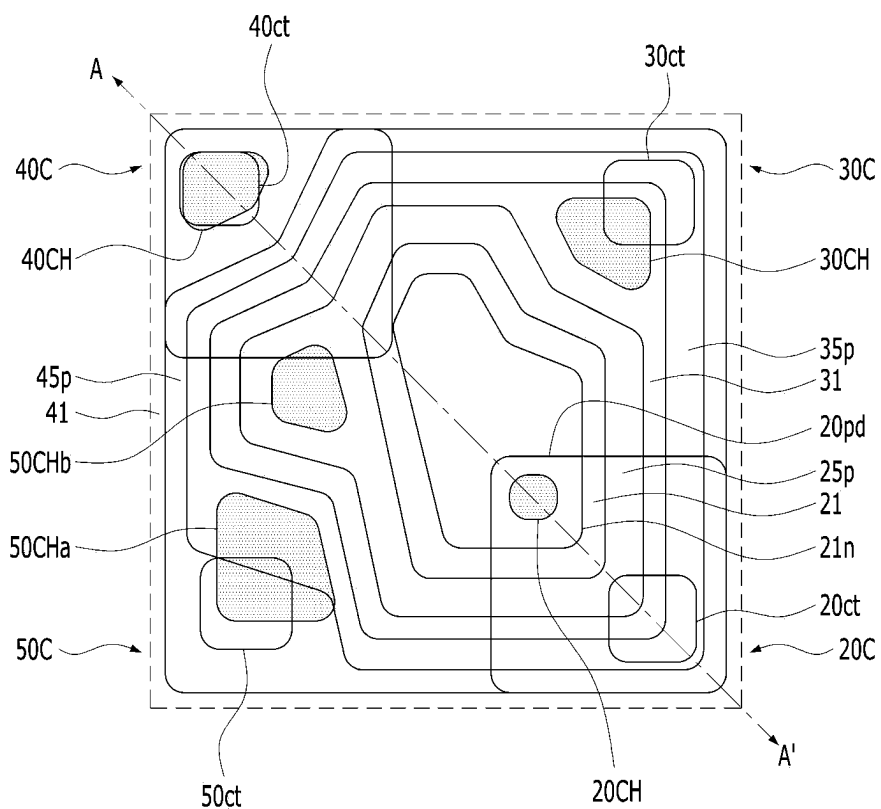


FIG. 7B

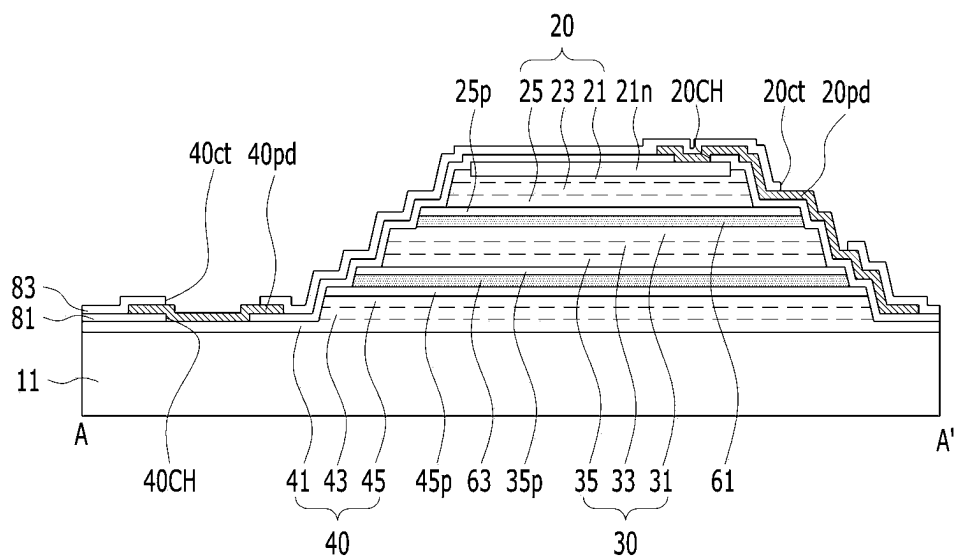


FIG. 8A

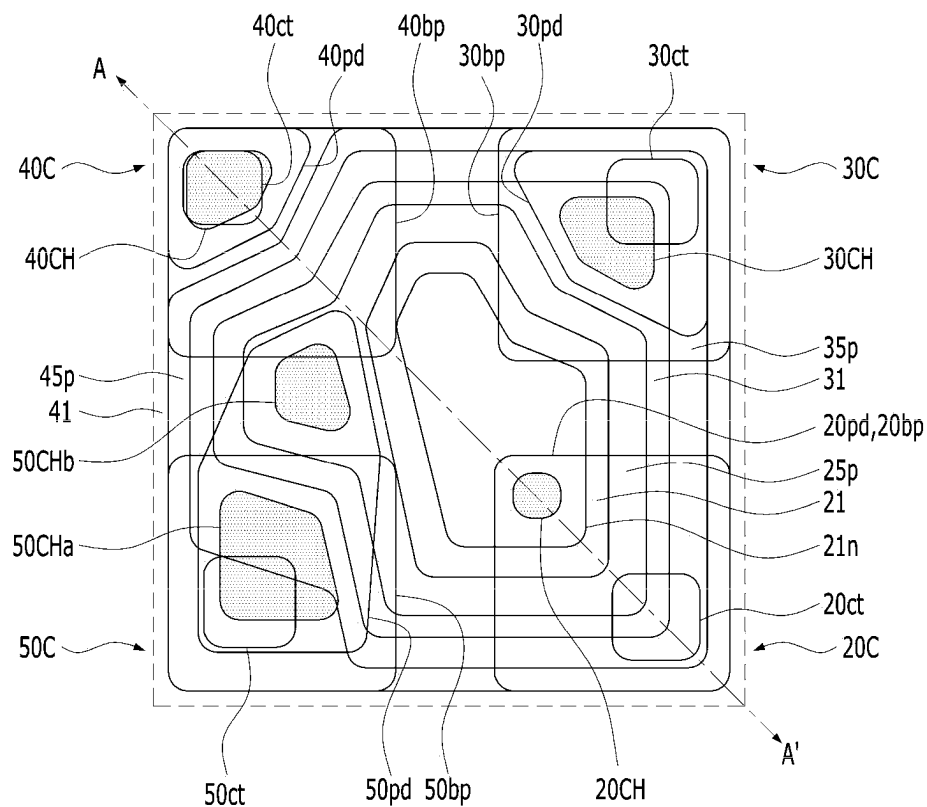


FIG. 8B

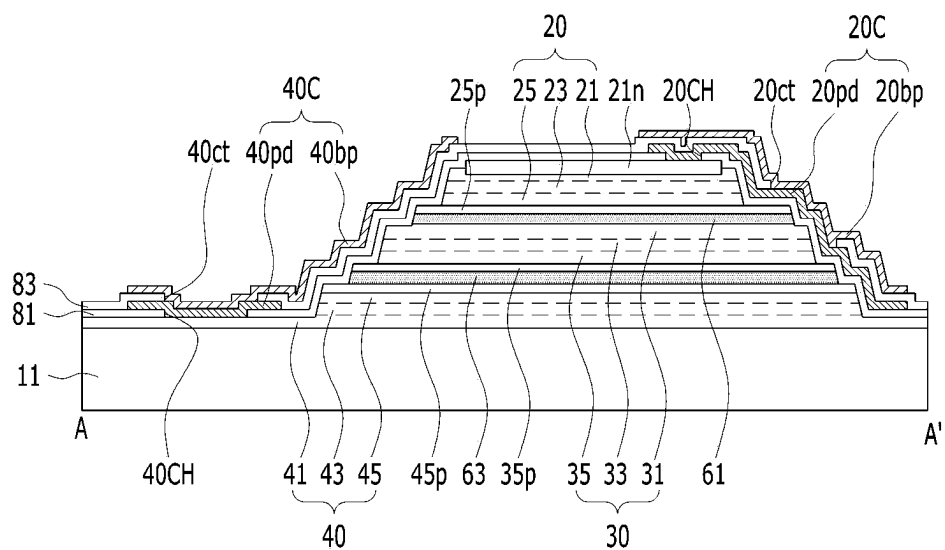


FIG. 9A

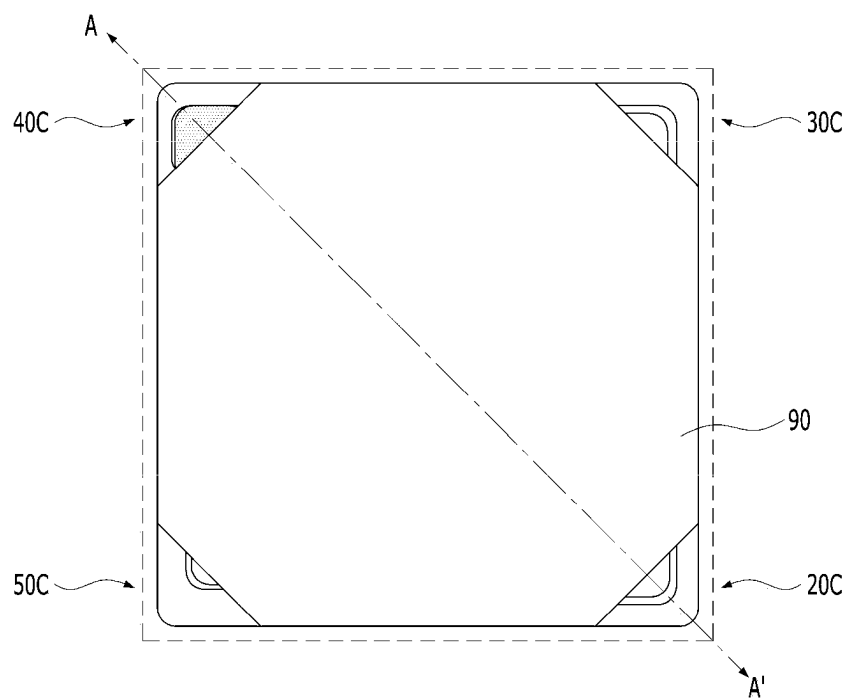


FIG. 9B

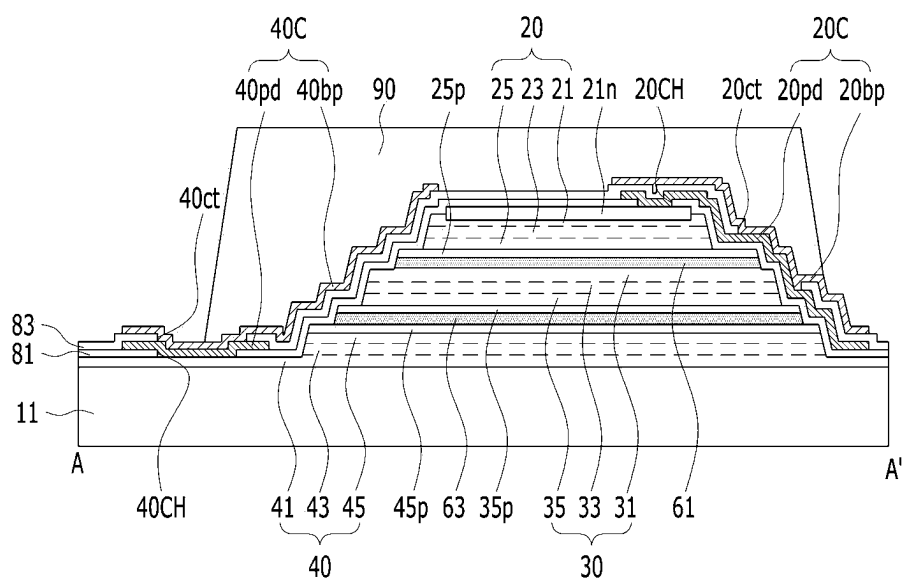


FIG. 10A

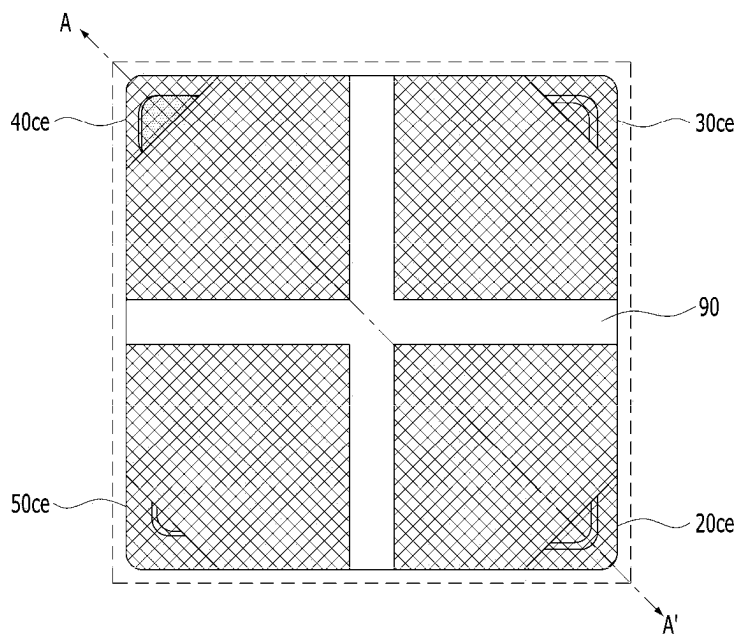


FIG. 10B

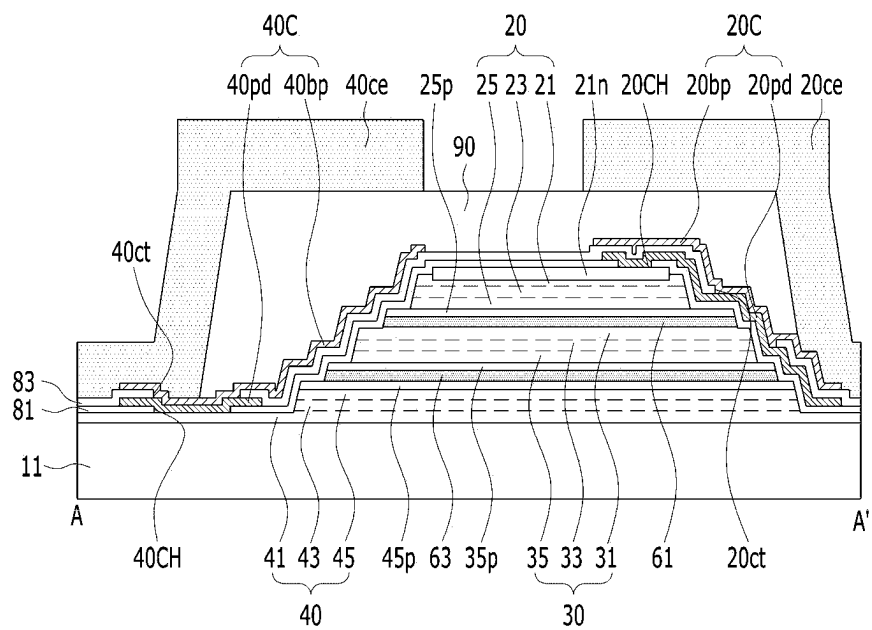


FIG. 11

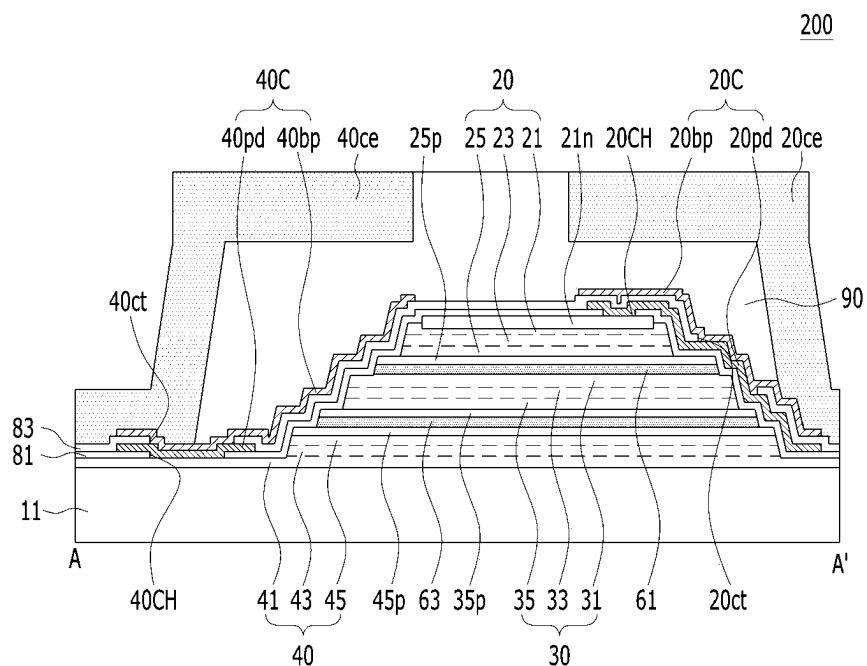


FIG. 12

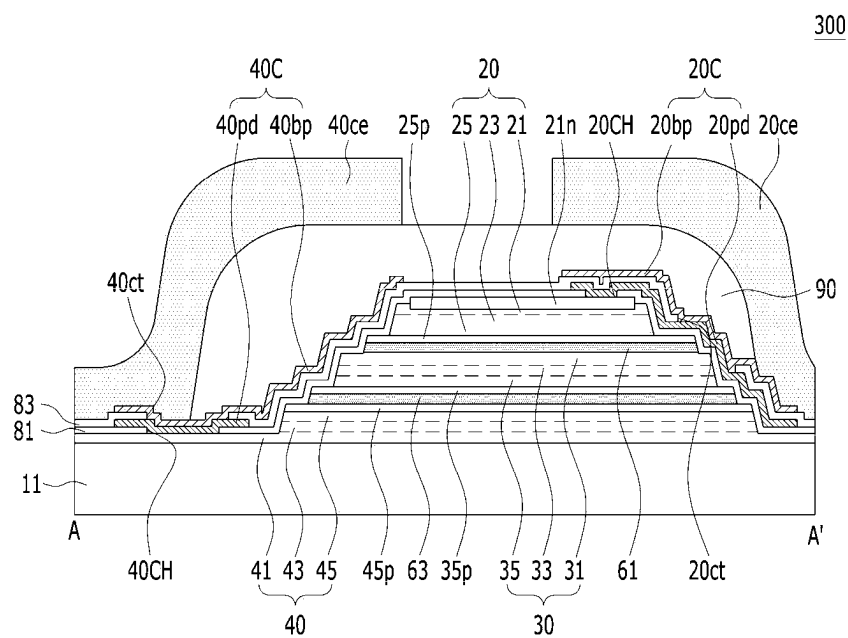


FIG. 13

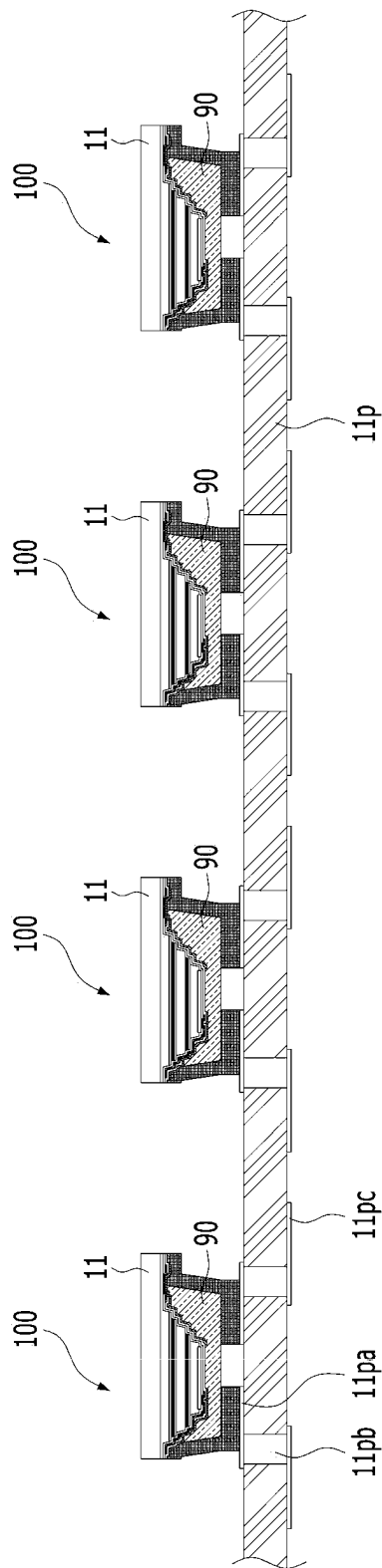


FIG. 14

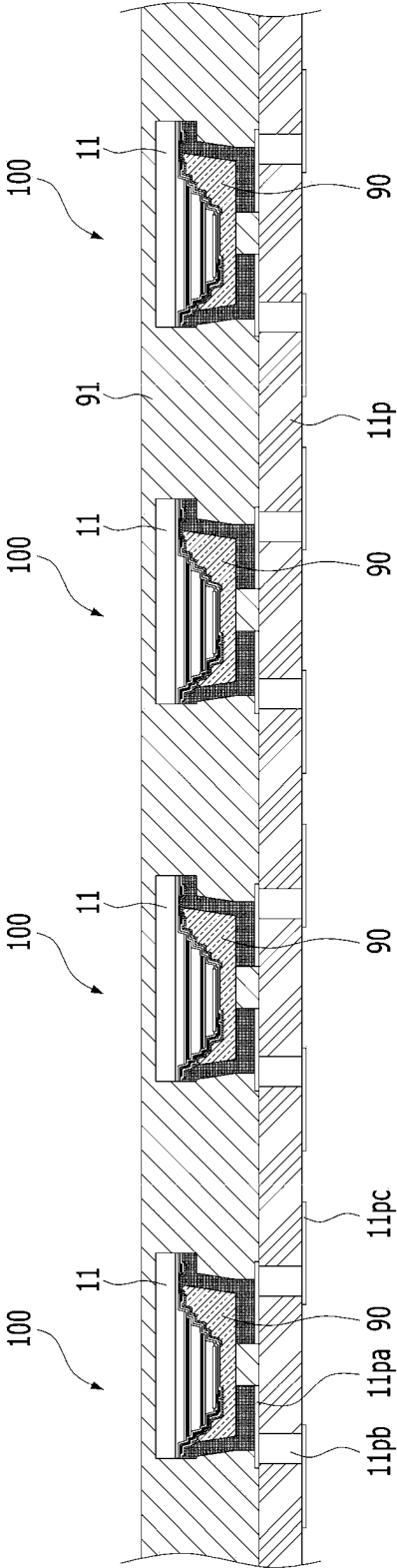




FIG. 15

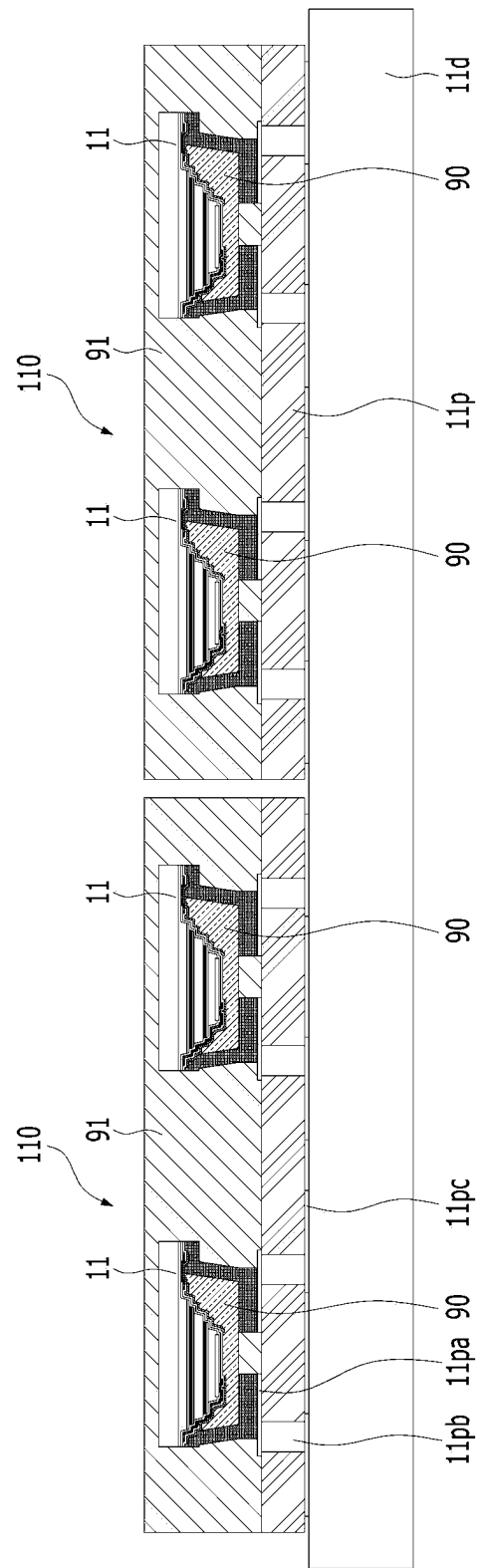


FIG. 16

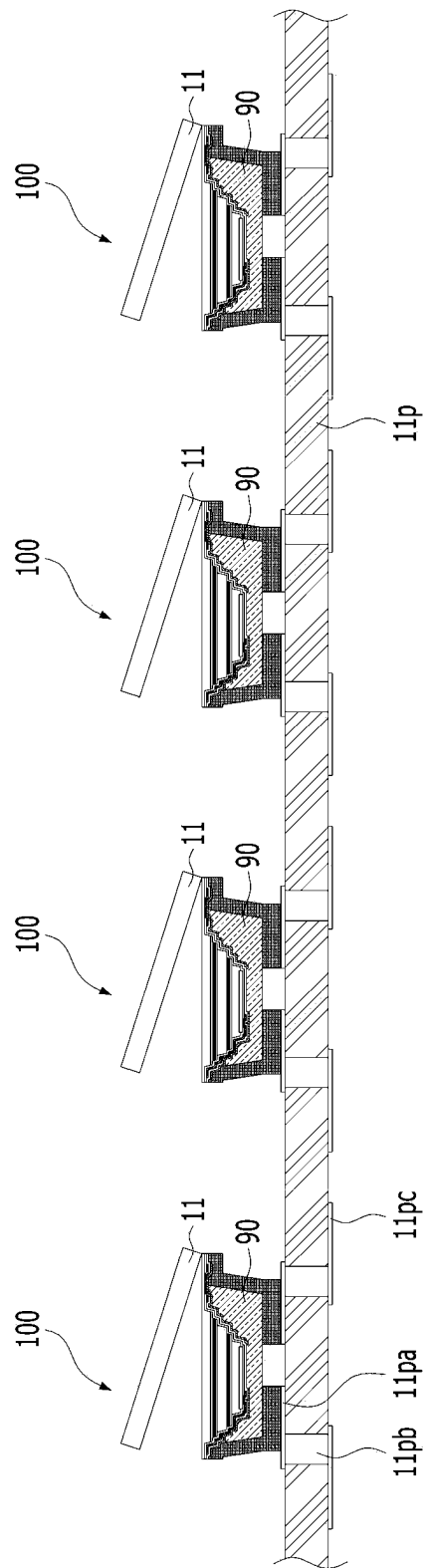
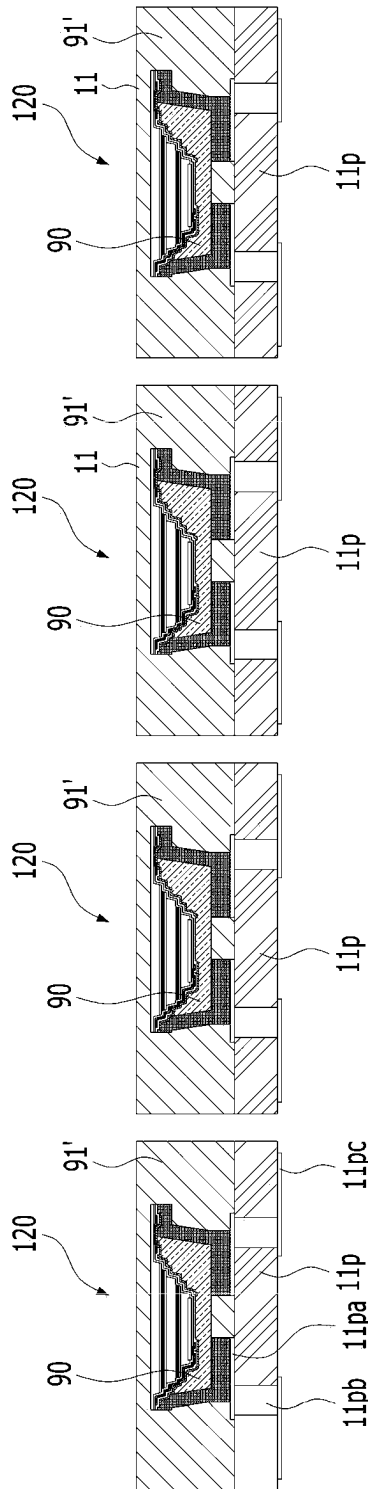


FIG. 17



## LED CHIP AND MANUFACTURING METHOD OF THE SAME

### CROSS-REFERENCE TO RELATED APPLICATIONS

[0001] This application is a continuation of and claims benefit under 35 U.S.C. § 120 to U.S. application Ser. No. 18/111,861 filed Feb. 20, 2023, which is a continuation of and claims benefit under 35 U.S.C. § 120 to U.S. application Ser. No. 16/852,522 filed Apr. 19, 2020 (now U.S. Pat. No. 11,587,914 issued Feb. 21, 2023), and claims the benefit of U.S. Provisional Application No. 62/847,852 filed May 14, 2019 and U.S. Provisional Application No. 62/869,972 filed Jul. 2, 2019, the entire contents of each of which are incorporated herein by reference.

### BACKGROUND

#### Field

[0002] Exemplary embodiments of the invention relate to a light emitting chip for a display and a manufacturing method of the same and, more specifically, to a micro light emitting chip having a stacked structure and a manufacturing method of the same.

#### Discussion of the Background

[0003] As an inorganic light source, light emitting diodes (LEDs) have been used in various technical fields, such as displays, vehicular lamps, general lighting, and the like. With advantages of long lifespan, low power consumption, and high response speed, light emitting diodes have been rapidly replacing an existing light source.

[0004] Light emitting diodes have been mainly used as backlight light sources in display apparatus. However, micro-LED displays have been recently developed that are capable of implementing an image directly using the light emitting diodes.

[0005] In general, a display apparatus implements various colors by using mixed colors of blue, green and, red light. The display apparatus includes pixels each having sub-pixels corresponding to blue, green, and red colors, and a color of a certain pixel may be determined based on the colors of the sub-pixels therein, and an image can be displayed through combination of the pixels.

[0006] Since LEDs can emit various colors depending upon its constituent materials, a display apparatus may typically have individual LED chips emitting blue, green, and red light arranged on a two-dimensional plane. However, when one LED chip is provided for each sub-pixel, the number of LED chips required to be mounted to form a display device becomes very large, e.g., over hundreds of thousands or millions, which may require a significant amount of time and complexity for the mounting process. Moreover, since the sub-pixels are arranged on the two-dimensional plane in a display apparatus, a relatively large area is required for one pixel including the sub-pixels for blue, green, and red light, and reducing the luminous area of each sub-pixel would deteriorate the brightness of the sub-pixels.

[0007] Moreover, micro-LEDs typically have a very small size with a surface area of about 10,000 square  $\mu\text{m}$  or less, and thus, various technical problems arise due to this small size. For example, an array of micro-LEDs is formed on a

substrate, and the micro-LEDs may be singularized into each micro-LED chip by cutting the substrate. The individualized micro-LED chips may then be mounted on another substrate, such as a printed circuit board, during which various transferring technologies may be employed. However, during these transferring steps, handling of each micro-LED chip is generally difficult due to its small size and its vulnerable structure.

[0008] The above information disclosed in this Background section is only for understanding of the background of the inventive concepts, and, therefore, it may contain information that does not constitute prior art.

### SUMMARY

[0009] Light emitting chips constructed according to the principles and some exemplary implementations of the invention are capable of protecting the light emitting stacked structures during various transferring processes.

[0010] Light emitting chips and a display using the same, e.g., micro-LEDs, constructed according to the principles and some exemplary implementations of the invention have a simplified structure that reduces the time for the mounting process during manufacture.

[0011] Additional features of the inventive concepts will be set forth in the description which follows, and in part will be apparent from the description, or may be learned by practice of the inventive concepts.

[0012] A light emitting chip according to an exemplary embodiment includes a first LED sub-unit, a second LED sub-unit disposed on the first LED sub-unit, a third LED sub-unit disposed on the second LED sub-unit, a passivation layer disposed on the third LED sub-unit, and a first connection electrode electrically connected to at least one of the first, second, and third LED sub-units, in which the first connection electrode and the third LED sub-unit form a first angle defined between an upper surface of the third LED sub-unit and an inner surface of the first connection electrode that is less than about  $80^\circ$ .

[0013] The first angle may be greater than about  $60^\circ$  and less than about  $70^\circ$ .

[0014] The passivation layer and the third LED sub-unit may form a second angle defined between the upper surface of the third LED sub-unit and an inner surface of the passivation layer that is less than about  $80^\circ$ .

[0015] The first connection electrode may have at least one surface having a curved shape.

[0016] The passivation layer may have a top surface facing away the third LED sub-unit and a side surface intersecting the top surface, and the first connection electrode may contact at least a portion of each of the top surface and the side surface of the passivation layer.

[0017] The first connection electrode may contact at least a portion of a top surface of the first LED sub-unit.

[0018] The first connection electrode may overlap at least a portion of each of the first, second, and third LED sub-units in a plan view.

[0019] At least a portion of the passivation layer may be exposed by the first connection electrode.

[0020] The passivation layer may expose at least a portion of a side surface of the first LED sub-unit.

[0021] The passivation layer may cover side surfaces of the second and third LED sub-units.

[0022] The passivation may expose at least a portion of a top surface of the first LED sub-unit.

[0023] The light emitting chip may further include a second connection electrode electrically connected to the first LED sub-unit, a third connection electrode electrically connected to the second LED sub-unit, and a fourth connection electrode electrically connected to the third LED sub-unit, in which the first connection electrode may be electrically connected to each of the first, second, and third sub-units, and each of the first, second, third, and fourth connection electrodes may have a curved shape.

[0024] Each of the first, second, third, and fourth connection electrodes may have a first portion disposed on a top surface of the passivation layer, and the passivation layer may not be disposed between the first portions of at least one of the first, second, third, and fourth connection electrodes.

[0025] The light emitting chip may further include a substrate, in which the first LED sub-unit may include a first LED light emitting stack, the second LED sub-unit may include a second LED light emitting stack, the third LED sub-unit may include a third LED light emitting stack, and the first, second, and third LED light emitting stacks may have successively smaller regions overlapping with the substrate.

[0026] At least one of the light emitting stacks may include a micro LED having a surface area less than about 10,000 square  $\mu\text{m}$ .

[0027] The passivation layer may have a substantially black color and include a photo-sensitive material.

[0028] A light emitting chip according to another exemplary embodiment includes a substrate having a substantially rectangular shape, a first LED sub-unit disposed on the substrate, a second LED sub-unit disposed on the first LED sub-unit, a third LED sub-unit disposed on the second LED sub-unit, a passivation layer disposed on the third LED sub-unit, and a first connection electrode electrically connected to at least one of the first, second, and third LED sub-units, in which the passivation layer exposes portions of the third LED sub-unit disposed around at least one corner of the substrate.

[0029] The first connection electrode may have a first portion contacting at least a portion of the first LED sub-unit and a second portion contacting at least a portion of a top surface of the passivation layer.

[0030] The first connection electrode and the substrate may form an angle defined between an upper surface of the third LED sub-unit and an inner surface of the first connection electrode that is less than about  $80^\circ$ .

[0031] The first connection electrode may be connected to each of the first, second, and third LED sub-units at one corner of the substrate exposed by the passivation layer.

[0032] It is to be understood that both the foregoing general description and the following detailed description are exemplary and explanatory and are intended to provide further explanation of the invention as claimed.

#### BRIEF DESCRIPTION OF THE DRAWINGS

[0033] The accompanying drawings, which are included to provide a further understanding of the invention and are incorporated in and constitute a part of this specification, illustrate exemplary embodiments of the invention, and together with the description serve to explain the inventive concepts.

[0034] FIG. 1A is a schematic, perspective view of a light emitting chip constructed according to an exemplary embodiment of the invention.

[0035] FIG. 1B is a plan view of the light emitting chip of FIG. 1A according to an exemplary embodiment showing underlying structures.

[0036] FIGS. 1C and 1D are cross-sectional views respectively taken along line A-A' and line B-B' of the light emitting chip of FIG. 1B according to an exemplary embodiment.

[0037] FIG. 1E is a SEM image of the light emitting chip of FIG. 1A according to an exemplary embodiment.

[0038] FIG. 2 is a schematic cross-sectional view of a light emitting stacked structure constructed according to an exemplary embodiment.

[0039] FIGS. 3A, 4A, 5A, 6A, 7A, 8A, 9A, and 10A are plan views illustrating a process of manufacturing the light emitting chip of FIG. 1A according to an exemplary embodiment.

[0040] FIGS. 3B, 4B, 5B, 6B, 7B, 8B, 9B, and 10B are cross-sectional views taken along line A-A' of its corresponding plan view shown in FIGS. 3A, 4A, 5A, 6A, 7A, 8A, 9B, and 10B according to an exemplary embodiment.

[0041] FIG. 11 is a cross-sectional view of a light emitting chip constructed according to another exemplary embodiment.

[0042] FIG. 12 is a cross-sectional view of a light emitting chip constructed according to still another exemplary embodiment.

[0043] FIGS. 13, 14, and 15 are cross-sectional views illustrating a process of manufacturing a light emitting package according to an exemplary embodiment.

[0044] FIGS. 16 and 17 are cross-sectional views schematically illustrating a process of manufacturing a light emitting package according to another exemplary embodiment.

#### DETAILED DESCRIPTION

[0045] In the following description, for the purposes of explanation, numerous specific details are set forth in order to provide a thorough understanding of various exemplary embodiments or implementations of the invention. As used herein “embodiments” and “implementations” are interchangeable words that are non-limiting examples of devices or methods employing one or more of the inventive concepts disclosed herein. It is apparent, however, that various exemplary embodiments may be practiced without these specific details or with one or more equivalent arrangements. In other instances, well-known structures and devices are shown in block diagram form in order to avoid unnecessarily obscuring various exemplary embodiments. Further, various exemplary embodiments may be different, but do not have to be exclusive. For example, specific shapes, configurations, and characteristics of an exemplary embodiment may be used or implemented in another exemplary embodiment without departing from the inventive concepts.

[0046] Unless otherwise specified, the illustrated exemplary embodiments are to be understood as providing exemplary features of varying detail of some ways in which the inventive concepts may be implemented in practice. Therefore, unless otherwise specified, the features, components, modules, layers, films, panels, regions, and/or aspects, etc. (hereinafter individually or collectively referred to as “elements”), of the various embodiments may be otherwise combined, separated, interchanged, and/or rearranged without departing from the inventive concepts.

**[0047]** The use of cross-hatching and/or shading in the accompanying drawings is generally provided to clarify boundaries between adjacent elements. As such, neither the presence nor the absence of cross-hatching or shading conveys or indicates any preference or requirement for particular materials, material properties, dimensions, proportions, commonalities between illustrated elements, and/or any other characteristic, attribute, property, etc., of the elements, unless specified. Further, in the accompanying drawings, the size and relative sizes of elements may be exaggerated for clarity and/or descriptive purposes. When an exemplary embodiment may be implemented differently, a specific process order may be performed differently from the described order. For example, two consecutively described processes may be performed substantially at the same time or performed in an order opposite to the described order. Also, like reference numerals denote like elements.

**[0048]** When an element, such as a layer, is referred to as being “on,” “connected to,” or “coupled to” another element or layer, it may be directly on, connected to, or coupled to the other element or layer or intervening elements or layers may be present. When, however, an element or layer is referred to as being “directly on,” “directly connected to,” or “directly coupled to” another element or layer, there are no intervening elements or layers present. To this end, the term “connected” may refer to physical, electrical, and/or fluid connection, with or without intervening elements. Further, the D1-axis, the D2-axis, and the D3-axis are not limited to three axes of a rectangular coordinate system, such as the x, y, and z-axes, and may be interpreted in a broader sense. For example, the D1-axis, the D2-axis, and the D3-axis may be perpendicular to one another, or may represent different directions that are not perpendicular to one another. For the purposes of this disclosure, “at least one of X, Y, and Z” and “at least one selected from the group consisting of X, Y, and Z” may be construed as X only, Y only, Z only, or any combination of two or more of X, Y, and Z, such as, for instance, XYZ, XYY, YZ, and ZZ. As used herein, the term “and/or” includes any and all combinations of one or more of the associated listed items.

**[0049]** Although the terms “first,” “second,” etc. may be used herein to describe various types of elements, these elements should not be limited by these terms. These terms are used to distinguish one element from another element. Thus, a first element discussed below could be termed a second element without departing from the teachings of the disclosure.

**[0050]** Spatially relative terms, such as “beneath,” “below,” “under,” “lower,” “above,” “upper,” “over,” “higher,” “side” (e.g., as in “sidewall”), and the like, may be used herein for descriptive purposes, and, thereby, to describe one element's relationship to another element(s) as illustrated in the drawings. Spatially relative terms are intended to encompass different orientations of an apparatus in use, operation, and/or manufacture in addition to the orientation depicted in the drawings. For example, if the apparatus in the drawings is turned over, elements described as “below” or “beneath” other elements or features would then be oriented “above” the other elements or features. Thus, the exemplary term “below” can encompass both an orientation of above and below. Furthermore, the apparatus may be otherwise oriented (e.g., rotated 90 degrees or at other orientations), and, as such, the spatially relative descriptors used herein interpreted accordingly.

**[0051]** The terminology used herein is for the purpose of describing particular embodiments and is not intended to be limiting. As used herein, the singular forms, “a,” “an,” and “the” are intended to include the plural forms as well, unless the context clearly indicates otherwise. Moreover, the terms “comprises,” “comprising,” “includes,” and/or “including,” when used in this specification, specify the presence of stated features, integers, steps, operations, elements, components, and/or groups thereof, but do not preclude the presence or addition of one or more other features, integers, steps, operations, elements, components, and/or groups thereof. It is also noted that, as used herein, the terms “substantially,” “about,” and other similar terms, are used as terms of approximation and not as terms of degree, and, as such, are utilized to account for inherent deviations in measured, calculated, and/or provided values that would be recognized by one of ordinary skill in the art.

**[0052]** Various exemplary embodiments are described herein with reference to sectional and/or exploded illustrations that are schematic illustrations of idealized exemplary embodiments and/or intermediate structures. As such, variations from the shapes of the illustrations as a result, for example, of manufacturing techniques and/or tolerances, are to be expected. Thus, exemplary embodiments disclosed herein should not necessarily be construed as limited to the particular illustrated shapes of regions, but are to include deviations in shapes that result from, for instance, manufacturing. In this manner, regions illustrated in the drawings may be schematic in nature and the shapes of these regions may not reflect actual shapes of regions of a device and, as such, are not necessarily intended to be limiting.

**[0053]** Unless otherwise defined, all terms (including technical and scientific terms) used herein have the same meaning as commonly understood by one of ordinary skill in the art to which this disclosure is a part. Terms, such as those defined in commonly used dictionaries, should be interpreted as having a meaning that is consistent with their meaning in the context of the relevant art and should not be interpreted in an idealized or overly formal sense, unless expressly so defined herein.

**[0054]** Hereinafter, exemplary embodiments of the present disclosure will be described in detail with reference to the accompanying drawings. As used herein, a light emitting stacked structure, a light emitting chip, or a light emitting package according to exemplary embodiments may include a micro-LED, which has a surface area less than about 10,000 square  $\mu\text{m}$  as known in the art. In other exemplary embodiments, the micro-LED's may have a surface area less than about 4,000 square  $\mu\text{m}$ , or less than about 2,500 square  $\mu\text{m}$ , depending upon the particular application.

**[0055]** FIG. 1A is a schematic view of a light emitting chip constructed according to an exemplary embodiment of the invention. FIG. 1B is a perspective plan view of the light emitting chip of FIG. 1A according to an exemplary embodiment, FIG. 1C and 1D are cross-sectional views respectively taken along line A-A' and line B-B' of the light emitting chip of FIG. 1B according to an exemplary embodiment, and FIG. 1E is a SEM image of the light emitting chip of FIG. 1A according to an exemplary embodiment.

**[0056]** Referring to FIGS. 1A and 1B, the light emitting chip 100 according to an exemplary embodiment includes a light emitting stacked structure, a first connection electrode 20ce, a second connection electrode 30ce, a third connection electrode 40ce, and a fourth connection electrode 50ce

formed on the light emitting stacked structure, and a passivation layer **90** surrounding the connection electrodes **20<sub>ce</sub>**, **30<sub>ce</sub>**, **40<sub>ce</sub>**, and **50<sub>ce</sub>**. An array of the light emitting chips **100** may be formed on the substrate **11**, and the light emitting chip **100** shown in FIG. 1A exemplarily shows one that has been singularized from the array, which will be described in more detail below. In some exemplary embodiments, the light emitting chip **100** including the light emitting stacked structure may be further processed to be formed as a light emitting package, which will be described in more detail later.

[0057] Referring to FIGS. 1A to 1D, the light emitting chip **100** according to the illustrated exemplary embodiment includes the light emitting stacked structure, which may include a first LED sub-unit, a second LED sub-unit, and a third LED sub-unit disposed on the substrate **11**. The first LED sub-unit may include a first light emitting stack **20**, the second LED sub-unit may include a second light emitting stack **30**, and the third LED sub-unit may include a third light emitting stack **40**. While the drawings show the light emitting stacked structure including three light emitting stacks **20**, **30**, and **40**, the inventive concepts are not limited to a particular number of light emitting stacks formed in the light emitting stacked structure. For example, in some exemplary embodiments, the light emitting stacked structure may include two or more light emitting stacks therein. Hereinafter, the light emitting chip **100** will be described with reference to a light emitting stacked structure including three light emitting stacks **20**, **30**, and **40** according to an exemplary embodiment.

[0058] The substrate **11** may include a light transmitting insulating material to transmit light therethrough. In some exemplary embodiments, however, the substrate **11** may be formed to be semi-transparent to transmit only light having a specific wavelength, or formed to be partially transparent to transmit only a portion of light having the specific wavelength. The substrate **11** may be a growth substrate capable of epitaxially growing the third light emitting stack **40** thereon, such as a sapphire substrate. However, the inventive concepts are not limited thereto, and in some exemplary embodiments, the substrate **11** may include various other transparent insulating materials. For example, the substrate **11** may include a glass, a quartz, a silicon, an organic polymer, or an organic-inorganic composite material, such as silicon carbide (SiC), gallium nitride (GaN), indium gallium nitride (InGaN), aluminum gallium nitride (AlGaN), aluminum nitride (AlN), gallium oxide (Ga<sub>2</sub>O<sub>3</sub>), or silicon substrate. As another example, the substrate **11** in some exemplary embodiments may be a printed circuit board or a composite substrate including electrical lines therein for providing light emitting signals and a common voltage to each of the light emitting stacks formed thereon.

[0059] Each of the first, second, and third light emitting stacks **20**, **30**, and **40** is configured to emit light towards the substrate **11**. As such, light emitted from the first light emitting stack **20**, for example, may pass through the second and third light emitting stacks **30** and **40**. According to an exemplary embodiment, light emitted from each of the first, second, and third light emitting stacks **20**, **30**, and **40** may have different wavelength bands from each other, and the light emitting stack that is disposed further away from the substrate **11** may emit light having a longer wavelength band. For example, the first, second, and third light emitting stacks **20**, **30**, and **40** may emit red light, green light, and

blue light, respectively. However, the inventive concepts are not limited thereto. As another example, the first, second, and third light emitting stacks **20**, **30**, and **40** may emit red light, blue light, and green light, respectively. As still another example, in another exemplary embodiment, one or more of the light emitting stacks may emit light having substantially the same wavelength band. As still another example, when the light emitting stacked structure includes a micro-LED, which has a surface area less than about 10,000 square  $\mu\text{m}$  as known in the art, or less than about 4,000 square  $\mu\text{m}$  or 2,500 square  $\mu\text{m}$  in other exemplary embodiments, a light emitting stack that is disposed further away from the substrate **11** may emit light having a shorter wavelength band than light emitted from the one disposed closer to the substrate **11**, without adversely affecting operation, due to the small form factor of a micro-LED. In this case, the micro-LED may be operated with low operating voltage, and thus, a separate color filter may not be required between the light emitting stacks. Hereinafter, the first, second, and third light emitting stacks **20**, **30**, and **40** will be exemplarily described as emitting red light, green light, and blue light, respectively, according to an exemplary embodiment.

[0060] The first light emitting stack **20** includes a first-type semiconductor layer **21**, an active layer **23**, and a second-type semiconductor layer **25**. According to an exemplary embodiment, the first light emitting stack **20** may include a semiconductor material that emits red light, such as aluminum gallium arsenide (AlGaAs), gallium arsenide phosphide (GaAsP), aluminum gallium indium phosphide (AlGaInP), and gallium phosphide (GaP), without being limited thereto.

[0061] A first upper contact electrode **21<sub>n</sub>** may be disposed on the first-type semiconductor layer **21** and form ohmic contact with the first-type semiconductor layer **21**, and a first lower contact electrode **25<sub>p</sub>** may be disposed under the second-type semiconductor layer **25** of the first light emitting stack **20**. According to an exemplary embodiment, a portion of the first-type semiconductor layer **21** may be patterned, and the first upper contact electrode **21<sub>n</sub>** may be disposed in the patterned area of the first-type semiconductor layer **21** to increase the level of ohmic contact therebetween. The first upper contact electrode **21<sub>n</sub>** may have a single-layer structure or a multi-layered structure, and may include Al, Ti, Cr, Ni, Au, Ag, Sn, W, Cu, or an alloy thereof, such as Au—Te alloy or an Au—Ge alloy, without being limited thereto. In an exemplary embodiment, the first upper contact electrode **21<sub>n</sub>** may have a thickness of about 100 nm, and include metal having high reflectance to increase light emission efficiency in a downward direction towards the substrate **11**.

[0062] The second light emitting stack **30** includes a first-type semiconductor layer **31**, an active layer **33**, and a second-type semiconductor layer **35**. According to an exemplary embodiment, the second light emitting stack **30** may include a semiconductor material that emits green light, such as indium gallium nitride (InGaN), gallium nitride (GaN), gallium phosphide (GaP), aluminum gallium indium phosphide (AlGaInP), and aluminum gallium phosphide (AlGaP), without being limited thereto. A second lower contact electrode **35<sub>p</sub>** is disposed under the second-type semiconductor layer **35** of the second light emitting stack **30**.

[0063] The third light emitting stack **40** includes a first-type semiconductor layer **41**, an active layer **43**, and a

second-type semiconductor layer **45**. According to an exemplary embodiment, the third light emitting stack **40** may include a semiconductor material that emits blue light, such as gallium nitride (GaN), indium gallium nitride (InGaN), and zinc selenide (ZnSe), without being limited thereto. A third lower contact electrode **45p** is disposed on the second-type semiconductor layer **45** of the third light emitting stack **40**.

[0064] According to an exemplary embodiment, each of the first-type semiconductor layers **21**, **31**, and **41** and each of the second-type semiconductor layers **25**, **35**, and **45** of the first, second, and third light emitting stacks **20**, **30**, and **40** may have a single-layer structure or a multi-layered structure, and in some exemplary embodiments, may include a superlattice layer. In addition, the active layers **23**, **33**, and **43** of the first, second, and third light emitting stacks **20**, **30**, and **40** may have a single quantum well structure or a multiple quantum well structure.

[0065] Each of the first, second, and third lower contact electrodes **25p**, **35p**, and **45p** may include a transparent conductive material to transmit light. For example, the lower contact electrodes **25p**, **35p**, and **45p** may include a transparent conductive oxide (TCO), such as tin oxide (SnO), indium oxide (InO<sub>2</sub>), zinc oxide (ZnO), indium tin oxide (ITO), and indium tin zinc oxide (ITZO), without being limited thereto.

[0066] A first adhesive layer **61** is disposed between the first light emitting stack **20** and the second light emitting stack **30**, and a second adhesive layer **63** is disposed between the second light emitting stack **30** and the third light emitting stack **40**. The first and second adhesive layers **61** and **63** may include a non-conductive material that transmits light. For example, the first and second adhesive layers **61** and **63** may each include an optical clear adhesive (OCA), which may include epoxy, polyimide, SU8, spin-on glass (SOG), benzocyclobutene (BCB), or others, without being limited thereto.

[0067] According to the illustrated exemplary embodiment, a first insulating layer **81** and a second insulating layer **83** are disposed on at least a portion of side surfaces of the first, second, and third light emitting stacks **20**, **30**, and **40**. At least one of the first and second insulating layers **81** and **83** may include various organic or inorganic insulating materials, such as polyimide, SiO<sub>2</sub>, SiN<sub>x</sub>, Al<sub>2</sub>O<sub>3</sub> or the like. For example, at least one of the first and second insulating layers **81** and **83** may include a distributed Bragg reflector (DBR). As another example, at least one of the first and second insulating layers **81** and **83** may include a black-colored organic polymer. In some exemplary embodiments, a metal reflection layer that is electrically floated may be further disposed on the first and second insulating layers **81** and **83** to reflect light emitted from the light emitting stacks **20**, **30**, and **40** towards the substrate **11**. In some exemplary embodiments, at least one of the first and second insulating layers **81** and **83** may have a single-layered or a multi-layered structure formed of two or more insulating layers having different refractive indices from each other.

[0068] According to an exemplary embodiment, each of the first, second, and third light emitting stacks **20**, **30**, and **40** may be driven independently. More particularly, one of the first and second-type semiconductor layers of each light emitting stack may be applied with a common voltage, and the other one of the first and second-type semiconductor layers of each light emitting stack may be applied with a

respective light emitting signal. For example, according to the illustrated exemplary embodiment, the first-type semiconductor layers **21**, **31**, and **41** of each light emitting stack may be an n-type, and the second-type semiconductor layers **25**, **35**, and **45** of each light emitting stack may be a p-type. In this case, the third light emitting stack **40** may have a reversed stacked sequence as compared to the first and second light emitting stacks **20** and **30**, such that the p-type semiconductor layer **45** is disposed on top of the active layer **43** to simplify the manufacturing process. Hereinafter, the first-type and second-type semiconductor layers may be interchangeably be referred to as p-type and n-type, respectively, according to the illustrated exemplary embodiment.

[0069] Each of the first, second, and third lower contact electrodes **25p**, **35p**, and **45p** respectively connected to the p-type semiconductor layers **25**, **35**, and **45** of the light emitting stacks may be connected to a fourth contact part **50C**, and the fourth contact part **50C** may be connected to the fourth connection electrode **50ce** to receive a common voltage from the outside. Meanwhile, the n-type semiconductor layers **21**, **31**, and **41** of the light emitting stacks may be connected to a first contact part **20C**, a second contact part **30C**, and a third contact part **40C**, respectively, to receive corresponding light emitting signals via the first, second, and third connection electrodes **20ce**, **30ce**, and **40ce**, respectively. In this manner, each of the first, second, and third light emitting stacks **20**, **30**, and **40** may be driven independently, while having a common p-type light emitting stacked structure.

[0070] While the light emitting chip **100** according to the illustrated exemplary embodiment has a common p-type structure, however, the inventive concepts are not limited thereto. For example, in some exemplary embodiments, the first-type semiconductor layers **21**, **31**, and **41** of each light emitting stack may be a p-type, and the second-type semiconductor layers **25**, **35**, and **45** of each light emitting stack may be an n-type to form a common n-type light emitting stacked structure. Furthermore, in some exemplary embodiments, the stacked sequence of each light emitting stack may be variously modified without being limited to that shown in the drawings. Hereinafter, the light emitting chip **100** according to the illustrated exemplary embodiment will be described with reference to the common p-type light emitting stacked structure.

[0071] According to the illustrated exemplary embodiment, the first contact part **20C** includes a first pad **20pd** and a first bump electrode **20bp** electrically connected to the first pad **20pd**. The first pad **20pd** is disposed on the first upper contact electrode **21n** of the first light emitting stack **20**, and is connected to the first upper contact electrode **21n** through a first contact hole **20CH** defined through the first insulating layer **81**. At least a portion of the first bump electrode **20bp** may overlap with the first pad **20pd**, and the first bump electrode **20bp** is connected to the first pad **20pd** through a first through-hole **20ct** with the second insulating layer **83** interposed therebetween in an overlapping area between the first bump electrode **20bp** and the first pad **20pd**. In this case, the first pad **20pd** and the first bump electrode **20bp** may have substantially the same shape to overlap with each other, without being limited thereto.

[0072] The second contact part **30C** includes a second pad **30pd** and a second bump electrode **30bp** electrically connected to the second pad **30pd**. The second pad **30pd** is disposed on the first-type semiconductor layer **31** of the



second light emitting stack **30**, and is connected to the first-type semiconductor layer **31** through a second contact hole **30CH** defined through the first insulating layer **81**. At least a portion of the second bump electrode **30bp** may overlap with the second pad **30pd**. The second bump electrode **30bp** may be connected to the second pad **30pd** through a second through hole **30ct** with the second insulating layer **83** interposed therebetween in an overlapping area between the second bump electrode **30bp** and the second pad **30pd**.

[0073] The third contact part **40C** includes a third pad **40pd** and a third bump electrode **40bp** electrically connected to the third pad **40pd**. The third pad **40pd** is disposed on the first-type semiconductor layer **41** of the third light emitting stack **40**, and is connected to the first-type semiconductor layer **41** through a third contact hole **40CH** defined through the first insulating layer **81**. At least a portion of the third bump electrode **40bp** may overlap with the third pad **40pd**. The third bump electrode **40bp** may be connected to the third pad **40pd** through a third through hole **40ct** with the second insulating layer **83** interposed therebetween in an overlapping area between the third bump electrode **40bp** and the third pad **40pd**.

[0074] The fourth contact part **50C** includes a fourth pad **50pd** and a fourth bump electrode **50bp** electrically connected to the fourth pad **50pd**. The fourth pad **50pd** is connected to the second-type semiconductor layers **25**, **35**, and **45** of the first, second, and third light emitting stacks **20**, **30**, and **40** through a first sub-contact hole **50CHa** and a second sub-contact hole **50CHb** defined on the first, second, and third lower contact electrodes **25p**, **35p**, and **45p** of the first, second, and third light emitting stacks **20**, **30**, and **40**. In particular, the fourth pad **50pd** is connected to the first lower contact electrode **25p** through the second sub-contact hole **50CHb**, and is connected to the second and third lower contact electrodes **35p** and **45p** through the first sub-contact hole **50CHa**. In this manner, since the fourth pad **50pd** can be connected to the second and third lower contact electrodes **35p** and **45p** through a single first sub-contact hole **50CHa**, a manufacturing process of the light emitting chip **100** may be simplified, and an area occupied by the contact holes in the light emitting chip **100** may be reduced. At least a portion of the fourth bump electrode **50bp** may overlap with the fourth pad **50pd**. The fourth bump electrode **50bp** is connected to the fourth pad **50pd** through a fourth through hole **50ct** with the second insulating layer **83** interposed therebetween in an overlapping area between the fourth bump electrode **50bp** and the fourth pad **50pd**.

[0075] According to an exemplary embodiment, the first, second, third, and fourth contact parts **20C**, **30C**, **40C**, and **50C** may be formed at various locations. For example, when the light emitting chip **100** has a substantially quadrangular shape as shown in the drawings, the first, second, third, and fourth contact parts **20C**, **30C**, **40C**, and **50C** may be disposed around each corner of the substantially quadrangular shape. However, the inventive concepts are not limited thereto, and in some exemplary embodiments, the light emitting chip **100** may be formed to have various shape, and the first, second, third, and fourth contact parts **20C**, **30C**, **40C**, and **50C** may be formed in other places depending on the shape of the light emitting device.

[0076] The first, second, third, and fourth pads **20pd**, **30pd**, **40pd**, and **50pd** are spaced apart from and insulated from each other. In addition, the first, second, third, and

fourth bump electrodes **20bp**, **30bp**, **40bp**, and **50bp** are spaced apart from and insulated from each other. According to an exemplary embodiment, each of the first, second, third, and fourth bump electrodes **20bp**, **30bp**, **40bp**, and **50bp** may cover at least a portion of side surfaces of the first, second, and third light emitting stacks **20**, **30**, and **40**, which may facilitate dissipation of heat generated from the first, second, and third light emitting stacks **20**, **30**, and **40** therethrough.

[0077] According to the illustrated exemplary embodiment, each of the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may have curved (convex when viewed from above) shapes that project away from the substrate **11**. More particularly, the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may substantially cover at least the sides of the light emitting stacked structure, while exposing the passivation layer **90** between the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce**. The connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may include metal, such as Cu, Ni, Ti, Sb, Zn, Mo, Co, Sn, Ag, or an alloy thereof, without being limited thereto. For example, in some exemplary embodiments, each of the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may include two or more metals or a plurality of different metal layers to reduce the stress applied thereto. In another exemplary embodiment, when the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** include Cu, an additional metal may be deposited or plated thereon to suppress oxidation of Cu. In some exemplary embodiments, when the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** include Cu/Ni/Sn, Cu may prevent Sn from being infiltrating into the light emitting stacked structure. In some exemplary embodiments, the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may include a seed layer for forming metal layer during a plating process, which will be described in more detail below.

[0078] As shown in the drawings, each of the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may have a substantially flat upper surface to facilitate an electrical connection between the light emitting stacked structure with external lines or electrodes to be described later. According to an exemplary embodiment, when the light emitting chip **100** includes a micro-LED, which has a surface area less than about 10,000 square  $\mu\text{m}$  as known in the art, or less than about 4,000 square  $\mu\text{m}$  or 2,500 square  $\mu\text{m}$  in other exemplary embodiments, the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may overlap a portion of at least one of the first, second, and third light emitting stacks **20**, **30**, and **40** as shown in the drawings. More particularly, the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may overlap at least one step formed in a side surface of the light emitting stacked structure. In this manner, heat generated from the light emitting stacked structure may be more efficiently dissipated to the outside.

[0079] The connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may overlap a side surface of each of the light emitting stacks **20**, **30**, and **40**, and may reflect light emitted from at least one or more light emitting stacks **20**, **30**, and **40**, thereby improving light efficacy. Since the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** substantially cover at least the sides of the light emitting stacked structure, the light emitting chip **100** may be protected from external impact. According to the illustrated exemplary embodiment, a side surface of the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may form an inclined angle  $G$  and  $G'$  with respect to the substrate **11**, to improve the adhesiveness between the light emitting chip **100** and a molding layer **91** which will be

described in more detail later. In an exemplary embodiment, the angle  $G$  and  $G'$  formed between at least one of the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$ , and  $50ce$  and the substrate  $11$  may be less than about  $80^\circ$ , and in some exemplary embodiments, the inclined angle  $G$  and  $G'$  may be about  $60^\circ$  to about  $70^\circ$  with respect to the substrate  $11$ .

[0080] In general, during manufacture, an array of a plurality of light emitting chips is formed on a substrate. The substrate may then be cut along scribing lines to singularize (to separate) each light emitting chip, and the light emitting chips may be transferred to another substrate or tape using various transferring technologies for further processing of the light emitting chips, such as packaging. In this case, when the light emitting chip includes connection electrodes, such as metal bumps or pillars that protrude outwardly from the light emitting structure, various problems may occur during subsequent processes, such as in the steps of transfer, due to the structure of the bare light emitting chip exposing the connection electrodes to the outside. Moreover, when the light emitting chips include a micro-LED, which has a surface area less than about 10,000 square  $\mu\text{m}$ , or less than about 4,000 square  $\mu\text{m}$ , or less than about 2,500 square  $\mu\text{m}$ , depending upon applications, handling of the light emitting chips may become more difficult due to its small form factor.

[0081] For example, when the connection electrodes have a substantially elongated shape, such as a bar, transferring the light emitting chips using a conventional vacuum method becomes difficult as the light emitting chip may not have sufficient suction area due to the protruding structure of the connection electrodes. Furthermore, the exposed connection electrodes may be directly impacted with various stresses during subsequent processes, such as when the connection electrodes contact a manufacturing device, which may cause damage to the structure of the light emitting chip. As another example, when the light emitting chip is transferred using a conventional pick-and-place method, an ejection pin may directly contact a portion of the light emitting chip disposed between the connection electrodes, and damage a top structure of the light emitting structure. In particular, the ejection pin may strike a center of the light emitting chip, and cause physical damage to the top light emitting stack of the light emitting chip. Such impact by the ejection pin to the light emitting chip is shown in FIG. 1E, where the center of the light emitting chip  $100$  is indented by the ejection pin.

[0082] According to the illustrated exemplary embodiment, the third and fourth connection electrodes  $40ce$  and  $50ce$  are shown as being asymmetrical to the first and second connection electrodes  $20ce$  and  $30ce$ . More particularly, each of the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$  and  $50ce$  may have a portion that does not overlap the passivation layer  $90$ , and FIGS. 1C and 1D, for example, show that those of the third and fourth connection electrodes  $40ce$  and  $50ce$  to be greater in area than those of the first and second connection electrodes  $20ce$  and  $30ce$  near two opposing ends of the substrate  $11$ . However, the inventive concepts are not limited thereto, and in some exemplary embodiments, each of the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$  and  $50ce$  may be symmetrical to each other. For example, a portion of each of the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$  and  $50ce$  that does not overlap the passivation layer  $90$  may have the same area as each other.

[0083] According to an exemplary embodiment, the passivation layer  $90$  may be formed on the light emitting

stacked structure. More particularly, as shown in FIG. 1A, the passivation layer  $90$  may be formed between the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$ , and  $50ce$ , and cover at least the sides of the light emitting stacked structure. According to the illustrated exemplary embodiment, the passivation layer  $90$  may expose side surfaces of the substrate  $11$ , first and second insulating layers  $81$  and  $83$ , and the third light emitting stack  $40$ . The passivation layer  $90$  may include an epoxy molding compound (EMC), which may be formed in various colors, such as black or transparent. However, the inventive concepts are not limited thereto. For example, in some exemplary embodiments, the passivation layer  $90$  may include a polyimide (PID), and in this case, the PID may be provided as a dry film rather than a liquid type to increase the level of flatness when applied to the light emitting stacked structure. In some exemplary embodiments, the passivation layer  $90$  may include a material that has photosensitivity. In this manner, the passivation layer  $90$  may protect the light emitting structure from an external impact that may be applied during subsequent processes, as well as providing a sufficient contact area to the light emitting chip  $100$  to facilitate its handling during subsequent transferring steps. In addition, the passivation layer  $90$  may prevent leakage of light towards a side surface of the light emitting chip  $100$ , so as to prevent or at least suppress interference of light emitted from adjacent light emitting chips  $100$ . According to an exemplary embodiment, side surfaces of the passivation layer  $90$  may be inclined, such that the connection electrodes  $20ce$ ,  $30ce$ ,  $40ce$ , and  $50ce$  formed thereon may have a curved shape, respectively.

[0084] FIG. 2 is a schematic cross-sectional view of a light emitting stacked structure according to an exemplary embodiment. The light emitting stacked structure according to the illustrated exemplary embodiment is substantially the same as that included in the light emitting chip  $100$  described above, and thus, repeated descriptions of substantially the same elements forming the light emitting stacked structure will be omitted to avoid redundancy.

[0085] Referring to FIG. 2, the first, second, and third lower contact electrodes  $25p$ ,  $35p$ , and  $45p$  according to an exemplary embodiment may be connected to a common line, to which the common voltage  $V_c$  is applied. Light emitting signal lines  $SR$ ,  $SG$ , and  $SB$  may be respectively connected to the first-type semiconductor layers  $21$ ,  $31$ , and  $41$  of the first, second, and third light emitting stacks  $20$ ,  $30$ , and  $40$ . In this case, the light emitting signal line is connected to the first-type semiconductor layer  $21$  of the first light emitting stack  $20$  through the first upper contact electrode  $21n$ . In the illustrated exemplary embodiment, a common voltage  $V_c$  is applied to the first, second, and third lower contact electrodes  $25p$ ,  $35p$ , and  $45p$  through the common line, and the light emitting signal is respectively applied to the first-type semiconductor layers  $21$ ,  $31$ , and  $41$  of the first, second, and third light emitting stacks  $20$ ,  $30$ , and  $40$  through the light emitting signal lines. In this manner, the first, second, and third light emitting stacks  $20$ ,  $30$ , and  $40$  may be individually controlled to selectively emit light.

[0086] Although FIG. 2 shows the light emitting stacked structure having the p-common structure, however, the inventive concepts are not limited thereto. For example, in some exemplary embodiments, the common voltage  $V_c$  may be applied to the first-type (or n-type) semiconductor layers  $21$ ,  $31$ , and  $41$  of the first, second, and third light emitting stacks  $20$ ,  $30$ , and  $40$ , and the light emitting signal may be

applied to the second-type (or p-type) semiconductor layers **25**, **35**, and **45** of the first, second, and third light emitting stacks **20**, **30**, and **40**.

**[0087]** The light emitting stacked structure according to an exemplary embodiment may display various colors of light depending on the operating status of each light emitting stack **20**, **30**, and **40**, whereas a conventional light emitting device may display various colors by a combination of multiple light emitting cells emitting a single color of light. More particularly, a conventional light emitting device generally includes light emitting cells that respectively emit different color of light, e.g., red, green, and blue, which are spaced apart from each other along a two dimensional plane, to implement a full color display. As such, a relatively large area may be occupied by the conventional light emitting cells. The light emitting stacked structure according to an exemplary embodiment, however, can emit different color of light by stacking a plurality of light emitting stacks **20**, **30**, **40**, thereby providing a high level of integration and implementing the full color through a significantly smaller area than that in the conventional light emitting device.

**[0088]** In addition, when the light emitting chips **100** are mounted to another substrate to manufacture a display device, for example, the number of chips to be mounted may be significantly reduced as compared to the conventional light emitting devices due to its stacked structure. As such, a manufacture of the display device that employs the light emitting chip **100** may be substantially simplified, especially when hundreds of thousands or millions of pixels are formed in one display device.

**[0089]** According to an exemplary embodiment, the light emitting stacked structure may further include various additional components to improve the purity and efficiency of light emitted therefrom. For example, in some exemplary embodiments, a wavelength pass filter may be formed between adjacent light emitting stacks to prevent or at least suppress light having a shorter wavelength from traveling towards a light emitting stack emitting a longer wavelength. In addition, in some exemplary embodiments, concave-convex portions may be formed on a light emitting surface of at least one of the light emitting stacks to balance the brightness of light between the light emitting stacks. For example, as green light generally has a higher visibility than red light and blue light, in some exemplary embodiments, the concave-convex portions may be formed on the light emitting stacks emitting red light or blue light to improve light efficiency thereof, thereby balancing the visibility between light emitted from the light emitting stacks.

**[0090]** Hereinafter, a method of forming the light emitting chip **100** will be described with reference to the drawings according to an exemplary embodiment.

**[0091]** FIGS. **3A**, **4A**, **5A**, **6A**, **7A**, **8A**, **9A**, and **10A** are plan views illustrating a process of manufacturing the light emitting chip of FIG. **1A** according to an exemplary embodiment. FIGS. **3B**, **4B**, **5B**, **6B**, **7B**, **8B**, **9B**, and **10B** are cross-sectional views taken along line A-A' of its corresponding plan view shown in FIGS. **3A**, **4A**, **5A**, **6A**, **7A**, **8A**, **9A**, and **10A** according to an exemplary embodiment.

**[0092]** Referring back to FIG. **2**, the first-type semiconductor layer **41**, the third active layer **43**, and the second-type semiconductor layer **45** of the third light emitting stack **40** may be sequentially grown on the substrate **11** by a metal organic chemical vapor deposition (MOCVD) method or a molecular beam epitaxy (MBE) method, for example. The

third lower contact electrode **45p** may be formed on the third p-type semiconductor layer **45** by a chemical vapor deposition method, for example, and may include a transparent conductive oxide (TCO), such as tin oxide (SnO), indium oxide (In<sub>2</sub>O<sub>3</sub>), zinc oxide (ZnO), indium tin oxide (ITO), indium tin zinc oxide (ITZO) or the like. When the third light emitting stack **40** emits blue light according to an exemplary embodiment, the substrate **11** may include Al<sub>2</sub>O<sub>3</sub> (e.g., sapphire substrate), and the third lower contact electrode **45p** may be a transparent conductive oxide (TCO), such as tin oxide (SnO), indium oxide (In<sub>2</sub>O<sub>3</sub>), zinc oxide (ZnO), indium tin oxide (ITO), indium tin zinc oxide (ITZO) or the like. The first and second light emitting stacks **20** and **30** may be similarly formed by sequentially growing the first-type semiconductor layer, the active layer, and the second-type semiconductor layer on a temporary substrate, respectively, and the lower contact electrode including a transparent conductive oxide (TCO) may be respectively formed on the second-type semiconductor layer by a chemical vapor deposition method or the like, for example. Then, the first and second light emitting stacks **20** and **30** may be adjoined to each other with the first adhesive layer **61** interposed therebetween, and at least one of the temporary substrates of the first and second light emitting stacks **20** and **30** may be removed by a laser lift off process, chemical process, mechanical process, or the like, for example. In this case, in some exemplary embodiments, a concave-convex portions may be formed on the exposed light emitting stack to improve light efficiency. Then, the first and second light emitting stacks **20** and **30** may be adjoined with the third light emitting stack **40** with the second adhesive layer **63** interposed therebetween, and the remaining one of the temporary substrates of the first and second light emitting stacks **20** and **30** may be removed by a laser lift off process, chemical process, mechanical process, or the like, for example. In this case, in some exemplary embodiments, a concave-convex portions may be formed on the remaining exposed light emitting stack to improve light efficiency. In this manner, the light emitting stacked structure shown in FIG. **2** may be formed.

**[0093]** Referring to FIGS. **3A** and **3B**, various portions of each of the first, second, and third light emitting stacks **20**, **30**, and **40** may be patterned via etching process or the like to expose portions of the first-type semiconductor layer **21**, first lower contact electrode **25p**, first-type semiconductor layer **31**, second lower contact electrode **35p**, third lower contact electrode **45p**, and first-type semiconductor layer **41**. According to the illustrated exemplary embodiment, the first light emitting stack **20** has the smallest area among the light emitting stacks **20**, **30**, and **40**. However, the inventive concepts are not limited to relative sizes of the light emitting stacks **20**, **30**, and **40**.

**[0094]** Referring to FIG. **4A** and **4B**, a portion of a top surface of the first-type semiconductor layer **21** of the first light emitting stack **20** may be patterned, such as via wet-etching, at which the first upper contact electrode **21n** may be formed. As described above, the first upper contact electrode **21n** may be formed in the patterned area of the first-type semiconductor layer **21** with a thickness of about 100 nm, for example, to improve ohmic contact therebetween.

**[0095]** Referring to FIGS. **5A** and **5B**, the first insulating layer **81** may be formed to cover the light emitting stacks **20**, **30**, and **40**, and portions of the first insulating layer **81** may

be removed to form the first, second, third, and fourth contact holes **20CH**, **30CH**, **40CH**, and **50CH**. The first contact hole **20CH** is defined on the first n-type contact electrode **21n** to expose a portion of the first n-type contact electrode **21n**.

[0096] The second contact hole **30CH** may expose a portion of the first-type semiconductor layer **31** of the second light emitting stack **30**. The third contact hole **40CH** may expose a portion of the first-type semiconductor layer **41** of the third light emitting stack **40**. The fourth contact hole **50CH** may expose portions of the first, second, and third lower contact electrodes **21p**, **31p**, and **41p**. The fourth contact hole **50CH** may include the first sub-contact hole **50CHa** exposing a portion of the first lower contact electrode **25p** and the second sub-contact hole **50CHb** exposing the second and third lower contact electrodes **35p** and **45p**. In some exemplary embodiments, however, a single first sub-contact hole **CH** may expose each of the first, second, and third lower contact electrodes **21p**, **31p**, and **41p**.

[0097] Referring to FIGS. 6A and 6B, the first, second, third, and fourth pads **20pd**, **30pd**, **40pd**, and **50pd** are formed on the first insulating layer **81** formed with the first, second, third, and fourth contact holes **20CH**, **30CH**, **40CH**, and **50CH**. The first, second, third, and fourth pads **20pd**, **30pd**, **40pd**, and **50pd** may be formed by, for example, forming a conductive layer on substantially the entire surface of the substrate **11**, and patterning the conductive layer using a photolithography process or the like.

[0098] The first pad **20pd** is formed to overlap an area where the first contact hole **20CH** is formed, such that the first pad **20pd** may be connected to the first upper contact electrode **21n** of the first light emitting stack **20** through the first contact hole **20CH**. The second pad **30pd** is formed to overlap an area where the second contact hole **30CH** is formed, such that the second pad **30pd** may be connected to the first-type semiconductor layer **31** of the second light emitting stack **30** through the second contact hole **30CH**. The third pad **40pd** is formed to overlap an area where the third contact hole **40CH** is formed, such that the third pad **40pd** may be connected to the first-type semiconductor layer **41** of the third light emitting stack **40** through the third contact hole **40CH**. The fourth pad **50pd** is formed to overlap with an area where the fourth contact hole **50CH** is formed, more particularly, where the first and second sub-contact holes **50CHa** and **50CHb** are formed, such that the fourth pad **50pd** may be connected to the first, second, and third lower contact electrodes **25p**, **35p**, and **45p** of the first, second, and third light emitting stacks **20**, **30**, and **40** through the first and second sub-contact holes **50CHa** and **50CHb**.

[0099] Referring to FIGS. 7A and 7B, the second insulating layer **83** may be formed on the first insulating layer **81**. The second insulating layer **83** may include silicon oxide and/or silicon nitride. However, the inventive concepts are not limited thereto, and in some exemplary embodiments, the first and second insulating layers **81** and **83** may include an inorganic material. The second insulating layer **83** is then patterned and to form the first, second, third, and fourth through holes **20ct**, **30ct**, **40ct**, and **50ct** therein.

[0100] The first through hole **20ct** formed on the first pad **20pd** exposes a portion of the first pad **20pd**. The second through hole **30ct** formed on the second pad **30pd** exposes a portion of the second pad **30pd**. The third through hole **40ct** formed on the third pad **40pd** exposes a portion of the

third pad **40pd**. The fourth through hole **50ct** formed on the fourth pad **50pd** exposes a portion of the fourth pad **50pd**. In the illustrated exemplary embodiment, the first, second, third, and fourth through holes **20ct**, **30ct**, **40ct**, and **50ct** may be respectively defined in areas where the first, second, third, and fourth pads **20pd**, **30pd**, **40pd**, and **50pd** are formed.

[0101] Referring to FIGS. 8A and 8B, the first, second, third, and fourth bump electrodes **20bp**, **30bp**, **40bp**, and **50bp** are formed on the second insulating layer **83** formed with the first, second, third, and fourth through holes **20ct**, **30ct**, **40ct**, and **50ct**. The first bump electrode **20bp** is formed to overlap an area where the first through hole **20ct** is formed, such that the first bump electrode **20bp** may be connected to the first pad **20pd** through the first through hole **20ct**. The second bump electrode **30bp** is formed to overlap an area where the second through hole **30ct** is formed, such that the second bump electrode **30bp** may be connected to the second pad **30pd** through the second through hole **30ct**. The third bump electrode **40bp** is formed to overlap an area where the third through hole **40ct** is formed, such that the third bump electrode **40bp** may be connected to the third pad **40pd** through the third through hole **40ct**. The fourth bump electrode **50bp** is formed to overlap with an area where the fourth through hole **50ct** is formed, such that the fourth bump electrode **50bp** is connected to the fourth pad **50pd** through the fourth through hole **50ct**. The first, second, third, and fourth bump electrodes **20bp**, **30bp**, **40bp**, and **50bp** may be formed by depositing a conductive layer on the substrate **11**, and patterning the conductive layer, for example, which may include at least one of Ni, Ag, Au, Pt, Ti, Al, and Cr, or the like.

[0102] Referring to FIG. 9A and 9B, the passivation layer **90** is formed on the light emitting stacked structure. As described above, the passivation layer **90** according to an exemplary embodiment may include an epoxy molding compound (EMC), which may be formed in various colors, such as black or transparent. However, the inventive concepts are not limited thereto, and in some exemplary embodiments, the passivation layer **90** may include a polyimide (PID), and in this case, the PID may be provided as a dry film rather than a liquid type to increase the level of flatness when applied to the light emitting stacked structure. In some exemplary embodiments, the passivation layer **90** may include a material that has photosensitivity.

[0103] According to an exemplary embodiment, a layer forming the passivation layer **90**, such as the one that includes a PID, may be deposited on substantially the entire outer surfaces of the light emitting stacked structure. The layer then may be patterned, such as via a lithography process, to expose at least a portion of each of the first bump electrode **20bp**, second bump electrode **30bp**, third bump electrode **40bp**, and fourth bump electrode **50bp**, to which the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** are connected to, respectively. The drawings show that the passivation layer **90** exposes each corner of the light emitting chip **100** in a plan view, however, the inventive concepts are not limited thereto. For example, the passivation layer **90** may expose various other portions of the light emitting chip **100**, as long as at least portions of the first bump electrode **20bp**, second bump electrode **30bp**, third bump electrode **40bp**, and fourth bump electrode **50bp** are exposed by the passivation layer **90**.

[0104] The passivation layer 90 may cover an upper surface of the light emitting stacked structure, such that the light emitting stacked structure, especially the first light emitting stack 20 disposed on the top of the structure, may be protected from external stress during manufacture. According to the illustrated exemplary embodiment, the passivation layer 90 may form an inclined angle G and G' (see FIGS. 1C and 1D) with respect to the substrate 11. For example, the angle G and G' formed between the passivation layer 90 and the substrate may be less than about 80°. When the inclined angle G and G' is greater than about 80°, the passivation layer 90 may not sufficiently cover steps formed on side surfaces of the light emitting stacked structure. In some exemplary embodiments, the inclined angle G and G' between the passivation layer 90 and the substrate 11 may be greater than about 60° and less than about 70°. In this manner, the connection electrodes 20ce, 30ce, 40ce, and 50ce to be formed on the passivation layer 90 may also be stably formed on the light emitting stacked structure. In addition, an edge between a top surface and a side surface of the passivation layer 90 may form a smooth angle, such that the connection electrodes 20ce, 30ce, 40ce, and 50ce to be formed thereon may have a substantially uniform thickness. However, the inventive concepts are not limited to, and in some exemplary embodiments, a substantially sharp edge may be formed between a top surface and a side surface of the passivation layer 90.

[0105] Referring to FIGS. 10A and 10B, the first, second, third, and fourth connection electrodes 20ce, 30ce, 40ce, and 50ce spaced apart from each other are formed on the passivation layer 90. Referring back to FIGS. 1B to 1D, the first, second, third, and fourth connection electrodes 20ce, 30ce, 40ce, and 50ce may be electrically connected to the first, second, third, and fourth bump electrodes 20bp, 30bp, 40bp, and 50bp, respectively, to transmit an external signal to each of the light emitting stacks 20, 30, and 40. More particularly, according to the illustrated exemplary embodiment, the first connection electrode 20ce may be connected to the first bump electrode 20bp, which is connected to the first upper contact electrode 21n through the first pad 20pd, to be electrically connected to the first-type semiconductor layer 21 of the first light emitting stack 20. The second connection electrode 30ce may be connected to the second bump electrode 30bp, which is connected to the second pad 30pd, to be electrically connected to the first-type semiconductor layer 31 of the second light emitting stack 30. The third connection electrode 40ce may be connected to the third bump electrode 40bp, which is connected to the third pad 40pd, to be electrically connected to the first-type semiconductor layer 41 of the third light emitting stack 40. The fourth connection electrode 50ce may be connected to the fourth bump electrode 50bp, which is connected to the fourth pad 50pd, to be electrically connected to the second-type semiconductor layers 25, 35, and 45 of the light emitting stacks 20, 30, and 40 via the first, second, and third lower contact electrodes 25p, 35p, and 45p, respectively.

[0106] A method of forming the first, second, third, and fourth connection electrodes 20ce, 30ce, 40ce, and 50ce is not particularly limited. For example, according to an exemplary embodiment, a conductive layer to be formed as the first, second, third, and fourth connection electrodes 20ce, 30ce, 40ce, and 50ce may be deposited on the passivation layer 90, and the conductive layer may be patterned by using a photo-lithography or the like, such that each of the

conductive layers overlaps a portion of the first bump electrode 20bp, second bump electrode 30bp, third bump electrode 40bp, and fourth bump electrode 50bp exposed by the passivation layer 90, respectively. The conductive layer (e.g., connection electrodes) according to an exemplary embodiment may include metal, such as Cu, Ni, Ti, Sb, Zn, Mo, Co, Sn, Ag, or an alloy thereof. In this case, a separate plating process may be omitted. In some exemplary embodiments, an additional metal may be deposited on the conductive layer, by an electroless nickel immersion gold (ENIG) or the like, to prevent or at least suppress oxidation of the connection electrodes 20ce, 30ce, 40ce, and 50ce.

[0107] According to the illustrated exemplary embodiment, each of the connection electrodes 20ce, 30ce, 40ce, and 50ce may have a curved shape that protrudes away from the substrate 11 to substantially cover the light emitting stacked structure and the passivation layer 90. As shown in the drawings, each of the connection electrodes 20ce, 30ce, 40ce, and 50ce may have a substantially flat upper surface to facilitate an electrical connection between the light emitting stacked structure and external lines or electrodes, as well as to increase the adhesiveness of the light emitting chip 100 to other elements, such as a PCB, during subsequent bonding and transferring steps. The connection electrodes 20ce, 30ce, 40ce, and 50ce may surround the at least a portion of each light emitting stack 20, 30, and 40 to protect the light emitting stacked structure, such that the light emitting chip 100 has a more stable structure that can withstand various subsequent processes along with the passivation layer 90. For example, when the substrate 11 is removed from the light emitting chip 100 in a subsequent process according to an exemplary embodiment, the connection electrodes 20ce, 30ce, 40ce, and 50ce that substantially surround the light emitting stacked structure may absorb at least a part of the stress that would otherwise be applied directly to the light emitting stacked structure, thereby protecting the light emitting chip 100 during manufacture.

[0108] Although the drawings show that the passivation layer 90 is not formed between the portions of the connection electrodes 20ce, 30ce, 40ce, and 50ce that are disposed on a top surface of the passivation layer 90, however, the inventive concepts are not limited thereto. For example, referring to FIG. 11, in a light emitting chip 200 according to another exemplary embodiment, the passivation layer 90 may be formed between the connection electrodes 20ce, 30ce, 40ce, and 50ce that are disposed on a top surface of the passivation layer 90, such that the upper surface of the passivation layer 90 may be substantially flush with the upper surfaces of the connection electrodes 20ce, 30ce, 40ce, and 50ce. In this manner, the adhesiveness of the light emitting chip 200 to the PCB or the like may be further strengthened during subsequent processes. A portion of the passivation layer 90 that is disposed between the connection electrodes 20ce, 30ce, 40ce, and 50ce may be formed before or after forming the connection electrodes 20ce, 30ce, 40ce, and 50ce. Since the constituent elements of the light emitting chip 200 according to the illustrated exemplary embodiment are substantially the same as those of the light emitting chip 100 described above, repeated descriptions of the substantially the same elements will be omitted to avoid redundancy.

[0109] Referring to FIG. 12, a light emitting chip 300 according to still another exemplary embodiment includes

connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** that have substantially curved shapes. According to the illustrated exemplary embodiment, the passivation layer **90** formed on the light emitting stacked structure may have a substantially rounded corners, such that the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** formed thereon may also be substantially rounded at corners thereof. In this manner, the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may be more stably disposed on the passivation layer **90**, as an interface therebetween forms a smooth angle, thereby improving the surface contact therebetween. Since the constituent elements of the light emitting chip **300** according to the illustrated exemplary embodiment are substantially the same as those of the light emitting chip **100** described above, repeated descriptions of the substantially the same elements will be omitted to avoid redundancy.

[0110] According to the illustrated exemplary embodiments, the third connection electrode **40ce** is shown as being asymmetrical to the first connection electrode **20ce**. More particularly, each of the connection electrodes **20ce**, **30ce**, **40ce** and **50ce** may have a portion that does not overlap the passivation layer **90**, and FIGS. **11** and **12**, for example, show that those of the third connection electrode **40ce** to be greater in area than those of the first connection electrode **20ce** near two opposing ends of the substrate **11**. However, the inventive concepts are not limited thereto, and in some exemplary embodiments, each of the connection electrodes **20ce**, **30ce**, **40ce** and **50ce** may be symmetrical to each other. For example, a portion of each of the connection electrodes **20ce**, **30ce**, **40ce** and **50ce** that does not overlap the passivation layer **90** may have the same area as each other.

[0111] FIGS. **13**, **14**, and **15** are cross-sectional views schematically illustrating a process of manufacturing a light emitting package according to an exemplary embodiment.

[0112] An array of the light emitting chips **100** described above may be singularized by cutting the substrate **11**, and each of the light emitting chips **100** may be transferred and be packaged via various methods known in the art.

[0113] Referring to FIG. **13**, the light emitting chips **100** may be mounted on a circuit board **11p**. According to an exemplary embodiment, the circuit board **11p** may include upper circuit electrodes **11pa**, lower circuit electrodes **11pc**, and middle circuit electrodes **11pb** disposed therebetween, which are electrically connected to each other. The upper circuit electrodes **11pa** may correspond to each of the first, second, third, and fourth connection electrodes **20ce**, **30ce**, **40ce**, and **50ce**, respectively. According to an exemplary embodiment, the lower circuit electrodes **11pc** of the light emitting chip **100** may be spaced apart from each other at a predetermined pitch, which may correspond to a pitch of electrodes of a final target device to which the light emitting chip **100** is to be mounted, such as a display device. In some exemplary embodiments, the upper circuit electrodes **11pa** may be surface treated by ENIG, to facilitate electrical connection to the connection electrodes of the light emitting chip **100** by being partially melt at high temperature.

[0114] According to an exemplary embodiment, the first, second, third, and fourth connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** of the light emitting chips **100** may be bonded to the upper circuit electrodes **11pa** of the circuit board **11p**, respectively, by an anisotropic conductive film (ACF) bonding, for example. When the light emitting chips **100** are bonded to the circuit board **11p** through ACF bonding, which may be performed at a lower temperature

than in other bonding methods, the light emitting chips **100** may be protected from being exposed to a high temperature during bonding. However, the inventive concepts are not limited to a particular bonding method. For example, in some exemplary embodiments, the light emitting chips **100** may be bonded to the circuit board **11p** using an anisotropic conductive paste (ACP), solder, ball grid area (BGA), or micro bumps including at least one of Cu and Sn. In this case, since the upper surfaces of the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** may provide a wider contacting area from its curved shape, the adhesiveness of the light emitting chips **100** to an anisotropic conductive film may be increased, thereby forming a more stable structure when bonded to the circuit board **11p**, and secure process margin during manufacture.

[0115] Referring to FIG. **14**, a molding layer **91** is formed between the light emitting chips **100**. According to an exemplary embodiment, the molding layer **91** may transmit a portion of light emitted from the light emitting chip **100**, and may also reflect, diffract, and/or absorb a portion of external light to prevent the external light from being reflected by the light emitting chip **100** towards a direction that may be visible to a user. The molding layer **91** may cover at least a portion of the light emitting chip **100** to protect the light emitting chip **100** from external moisture and stress, for example. In this manner, together with the passivation layer **90** formed on the light emitting chip **100**, the molding layer **91** may provide an additional protection to the light emitting package by further reinforcing its structure.

[0116] According to an exemplary embodiment, when the molding layer **91** covers a top surface of the substrate **11** facing away the circuit board **11p**, the molding layer **91** may have a thickness less than about 100  $\mu\text{m}$  to at least transmit 50% of light emitted from the light emitting chip **100**. In an exemplary embodiment, the molding layer **91** may include an organic or an inorganic polymer. In some exemplary embodiments, the molding layer **91** may additionally include pillars, such as silica or alumina. In some exemplary embodiments, the molding layer **91** may include the same material as the passivation layer **90**. The molding layer **91** may be formed through various methods known in the art, such as lamination, plating, and/or printing methods. For example, the molding layer **91** may be formed by a vacuum laminate process, in which an organic polymer sheet is disposed on the light emitting chip **100**, and high temperature and pressure are applied in vacuum, to improve light uniformity by providing a substantially planar top surface of the light emitting package.

[0117] Referring to FIG. **15**, the light emitting chips **100** formed on the circuit board **11p** and covered with the molding layer **91** may be cut in a desired configuration to be formed as a light emitting package **110**. For example, the light emitting package **110** may include a single light emitting chip **100** therein or may include a plurality of light emitting chips therein, such as in 2x2 arrangement. However, the inventive concepts are not limited to a particular number of light emitting chips formed in the light emitting package **110**. For example, in some exemplary embodiments, the light emitting package **110** may include one or more light emitting chips **100** formed on the circuit board **11p**. In addition, the inventive concepts are not limited to a particular arrangement of one or more light emitting chips **100** in the light emitting package **110**. For example, one or

more light emitting chips **100** in the light emitting package **110** may be arranged in  $n \times m$  arrangement, where  $n$  and  $m$  are natural numbers. According to an exemplary embodiment, the circuit board **11p** may include scan lines and data lines to independently drive each of the light emitting chips **100** included in the light emitting package **110**.

[0118] Referring to FIG. 16, the light emitting packages **110** may be mounted on a target substrate **11d** of a final device, such as a display device. The target substrate **11d** may include target electrodes corresponding to the lower circuit electrodes **11pc** of the light emitting package **110**, respectively. According to an exemplary embodiment, the display device may include a plurality of pixels, and each of the light emitting chips **100** may be disposed to correspond to each pixel. More particularly, each of the light emitting stacks of the light emitting chip **100** according to the exemplary embodiments may correspond to each sub-pixel of one pixel. Since the light emitting chip **100** includes vertically stacked light emitting stacks **20**, **30**, and **40**, the number of chips that would need to be transferred for each sub-pixel may be substantially reduced than that in a conventional light emitting device. In addition, since the connection electrodes **20ce**, **30ce**, **40ce**, and **50ce** according to the exemplary embodiments are curved and substantially surrounds the passivation layer **90** covering the light emitting stacked structure, the light emitting chip **100** may be protected from external stress. Although the light emitting chips **100** have been described above as being mounted on the circuit board **11p**, and then packaged to be mounted on a final device, such as a display panel, however, the inventive concepts are not limited thereto. For example, in some exemplary embodiments, the light emitting chips **100** may be covered with or without the molding layer **91**, and may be directly mounted on the final device, such as a display panel.

[0119] FIGS. 16 and 17 are cross-sectional views schematically illustrating a process of manufacturing a light emitting package according to another exemplary embodiment.

[0120] Referring back to FIG. 13, according to another exemplary embodiment, the substrate **11** attached on the light emitting chips **100** may be removed, as shown in FIG. 16, by a laser lift off (LLO) process, chemical process, mechanical process, or the like. In this case, since the light emitting chips **100** constructed according to the principles of the invention have a reinforced internal structure as described above, the light emitting stacked structures included in the light emitting chips **100** may be protected from external stress even when the substrate **11** is removed.

[0121] According to an exemplary embodiment, when the substrate **11** is a patterned sapphire substrate, concave-

convex portions may be formed on the first-type semiconductor layer **41** of the third light emitting stack **40** that contacted the substrate **11** to improve light efficiency. In another exemplary embodiment, concave-convex portions may be formed on the first-type semiconductor layer **41** of the third light emitting stack **40** by etching or patterning, as known in the art.

[0122] Referring to FIG. 17, a molding layer **91'** is formed between the light emitting chips **100**, and the light emitting chips **100** may be cut in a desired configuration to provide a light emitting package **120**. According to an exemplary embodiment, the molding layer **91'** may cover the light emitting chip **100**. The molding layer **91'** is substantially the same as the molding layer **91** described above, and the arrangements of the light emitting chips **100** in the light emitting package **120** are substantially same as the light emitting package **110** described above, and thus, repeated descriptions thereof will be omitted to avoid redundancy.

[0123] Although certain exemplary embodiments and implementations have been described herein, other embodiments and modifications will be apparent from this description. Accordingly, the inventive concepts are not limited to such embodiments, but rather to the broader scope of the appended claims and various obvious modifications and equivalent arrangements as would be apparent to a person of ordinary skill in the art.

What is claimed is:

1. A light emitting device, comprising:

a board;

a first stacked structure configured to emit light having a first wavelength;

a second stacked structure configured to emit light having a second wavelength;

a third stacked structure configured to emit light having a third wavelength;

a first connection electrode electrically connected to the first stacked structure, the second stacked structure, and the third stacked structure; and

a protection material covering at least a portion of the first connection electrode,

wherein each of the first, second, and third stacked structures is configured to selectively emit light while being connected to the first connection electrode and

wherein the protection material is configured to transmit at least 50% of light having the first wavelength, light having the second wavelength, and light having the third wavelength upon operation of each of the first, second, and third stacked structures.

\* \* \* \* \*